

3D Integration & New Pixel Developments (focus: High Luminosity LHC)

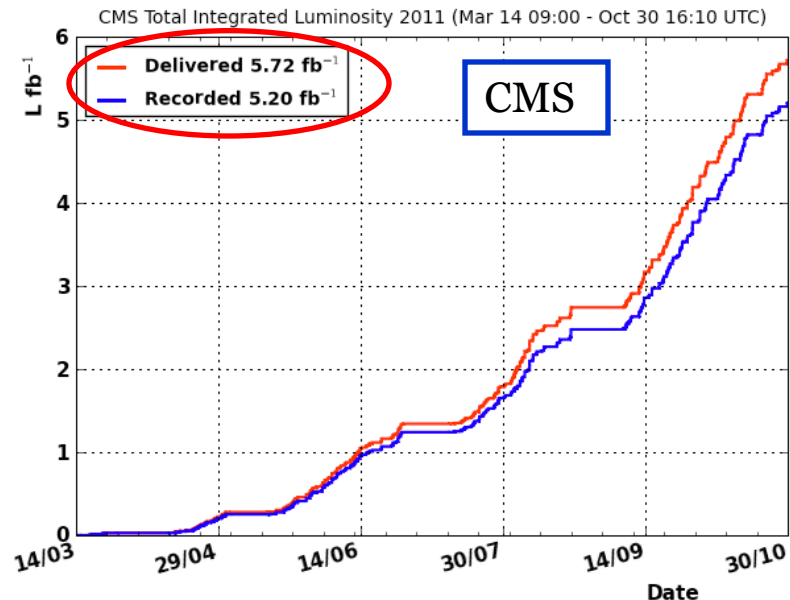
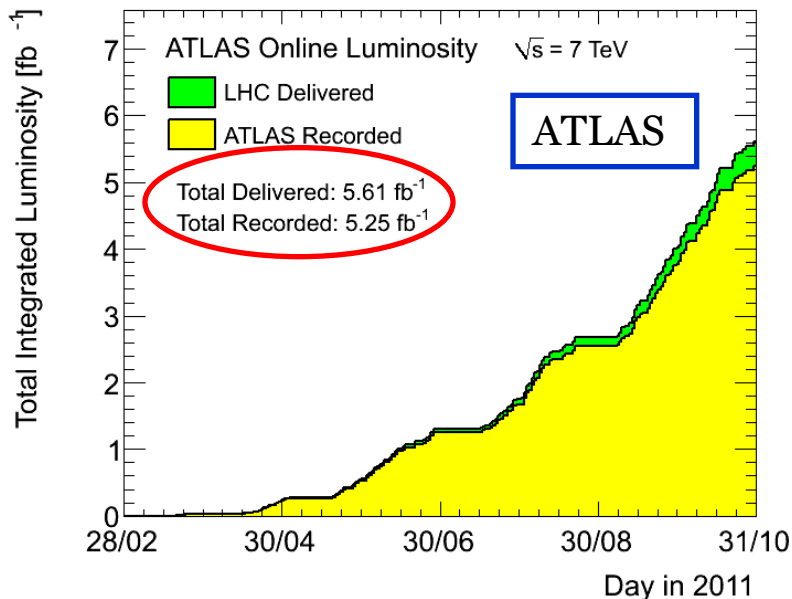
Marlon Barbero (Bonn University)

March 15th 2012

5th Detector Workshop Helmholtz Alliance, Bonn, March 14th -16th 2012

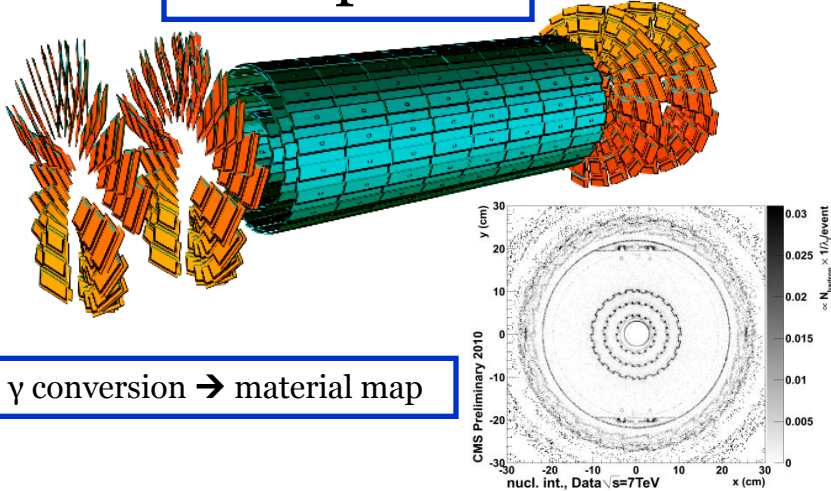
Introduction

- LHC, performing superbly.
- 2011: higher than expected luminosity
- 2011 a great LHC year...
and more to come for 2012!



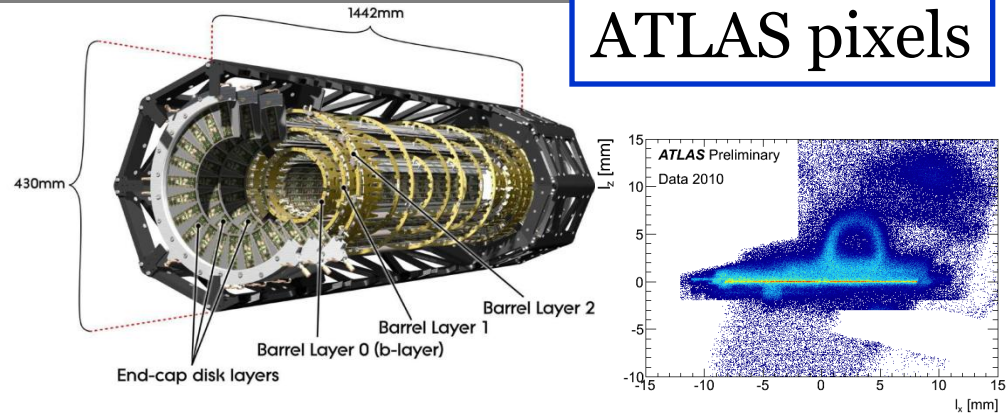
Current inner detectors at LHC

CMS pixels



γ conversion \rightarrow material map

ATLAS pixels



γ conversion \rightarrow material map

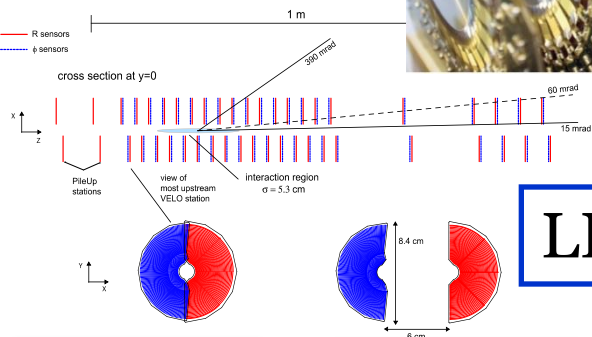
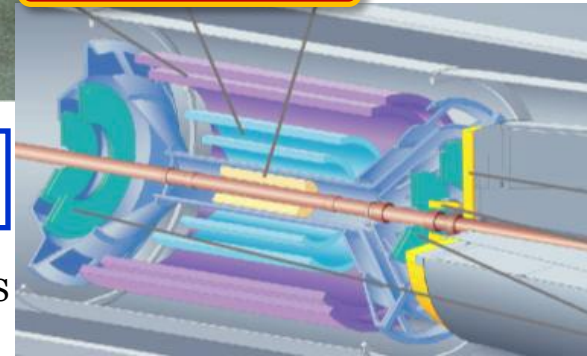


LHCb VELO



Alice Pixel

Strip Drift Pixel



Closed for physics

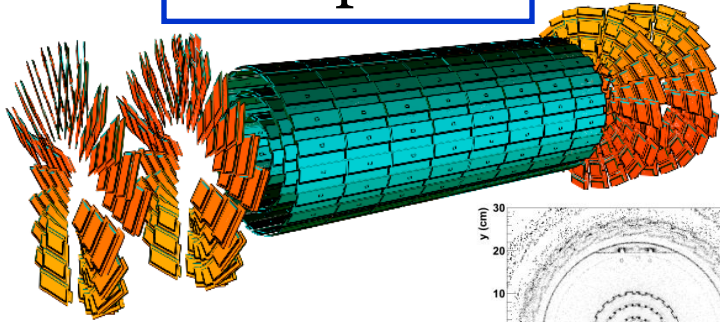


Open during injection

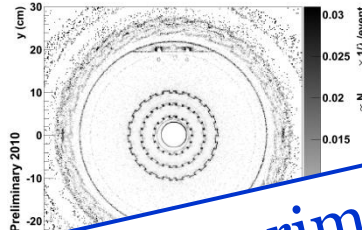
Arbero, Uni Bonn, 3D and NewPix, HHA Detektor WS

Current inner detectors at LHC

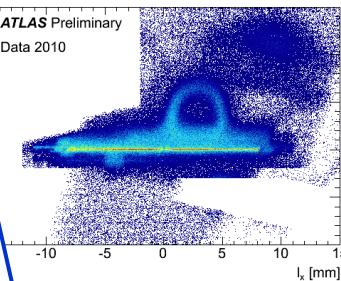
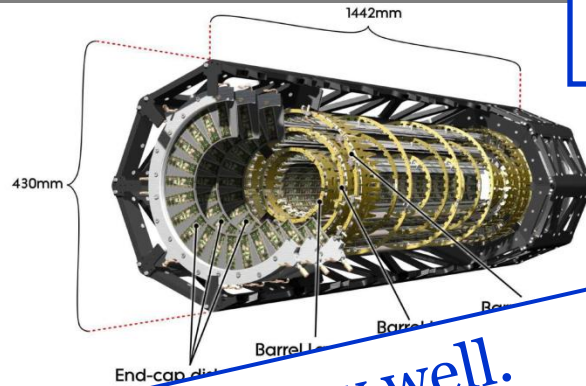
CMS pixels



γ conversion \rightarrow material map

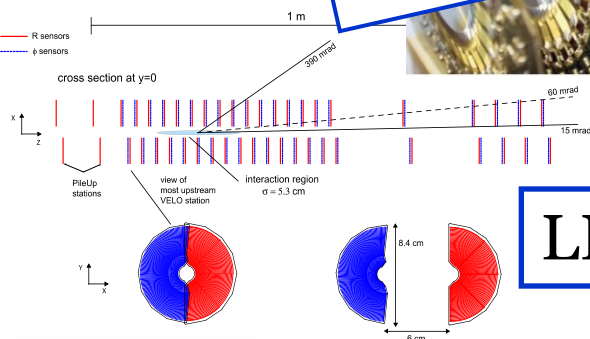


ATLAS pixels



γ conversion \rightarrow material map

The 4 main experiments work very well.
Operational channel in all sub-detectors:
 \rightarrow typ $\sim > 97\%$ or better for all!

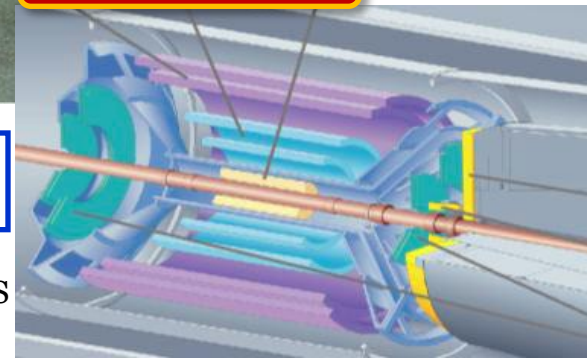


LHCb VELO



Strip Drift Pixel

Alice Pixel



Closed for physics



Open during injection

arbero, Uni Bonn, 3D and NewPix, HHA Detektor WS

Needs for pixel upgrade for HL?

- High Luminosity LHC challenges for inner layers:
 - Higher **hit rate**.
 - Higher **radiation levels**.

... while needing

- **High resolution**.
- **Low material**.

L. Gonella's talk

→ leads to high performance for physics!

ATLAS FE-I4 in 130nm CMOS

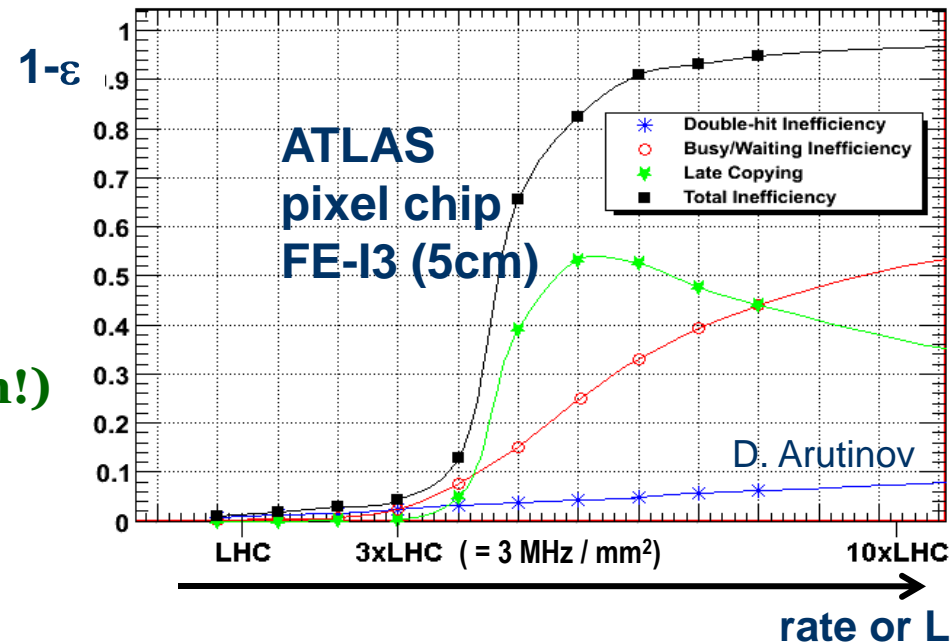
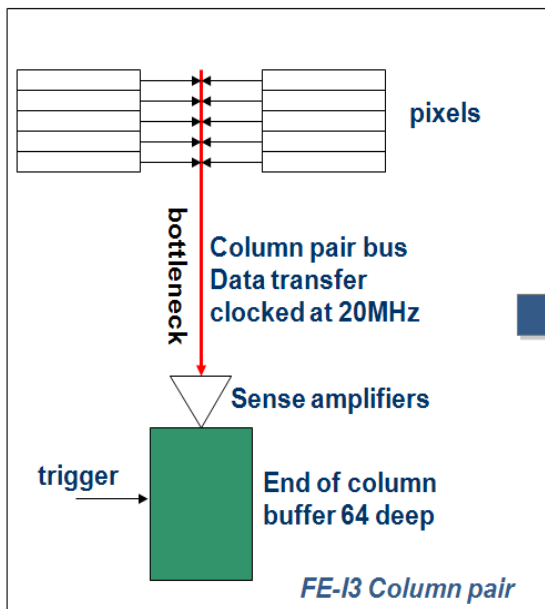
- Focus of ATLAS pixel FE designers' activity since ~2008.
- **Features:**
 - Smaller pixel $50 \times 250 \mu\text{m}^2$ (resolution up + reduced X-section), big array $-20 \times 17 \text{mm}^2$ active- (simpler module, less material).
 - Low power (analog / digital array), low noise (digital / analog separation, T3 deep nwell), high radiation tolerance (130nm).
 - New pixel digital organization: buffers in 4-pixel region (only triggered hits are transferred to EoDC) → efficient at high rate.
 - Data reformatting + 160Mb/s data transmission → high rate data transmission.
- Full size 1st proto back fall 2010, performs very well.
- Production version for IBL back Dec. 2011.
 - Works good (but not all parts thoroughly tested yet).

HL-LHC data rates & next ATLAS FE

Hit inefficiency rises steeply with the hit rate

Bottleneck: congestion in double column readout

⇒ **more local in-pixel storage (130nm!)**
⇒ **>99% of hits are not triggered**
⇒ **don't move them -> not blocking**



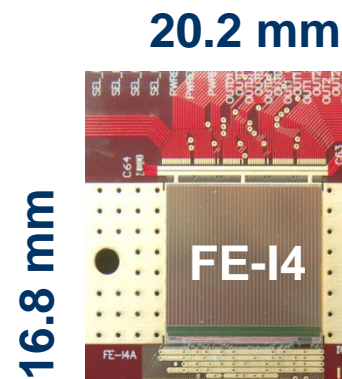
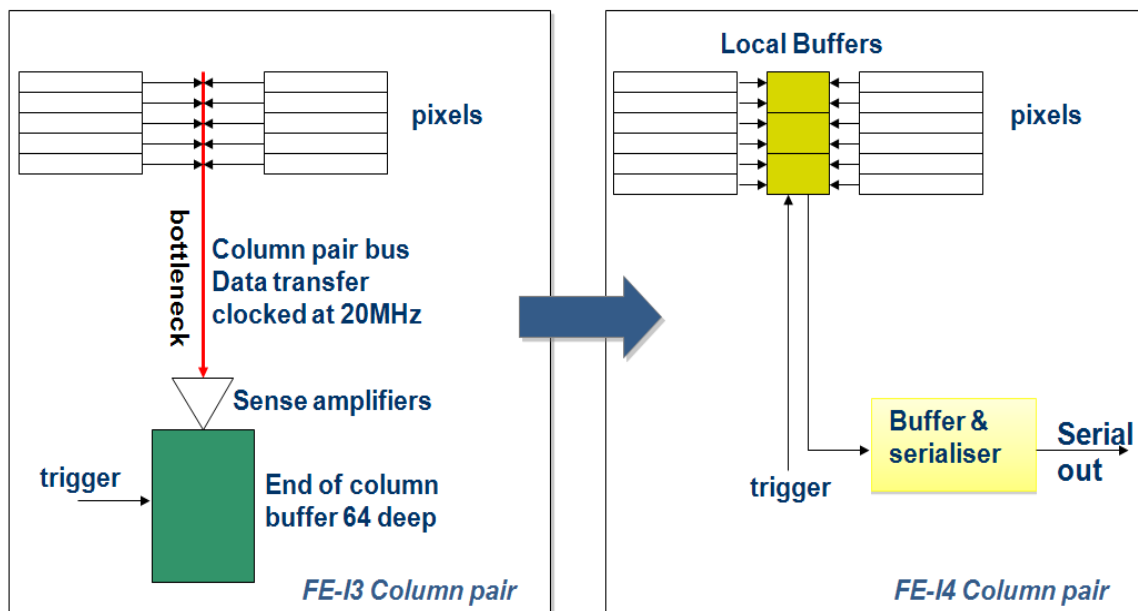
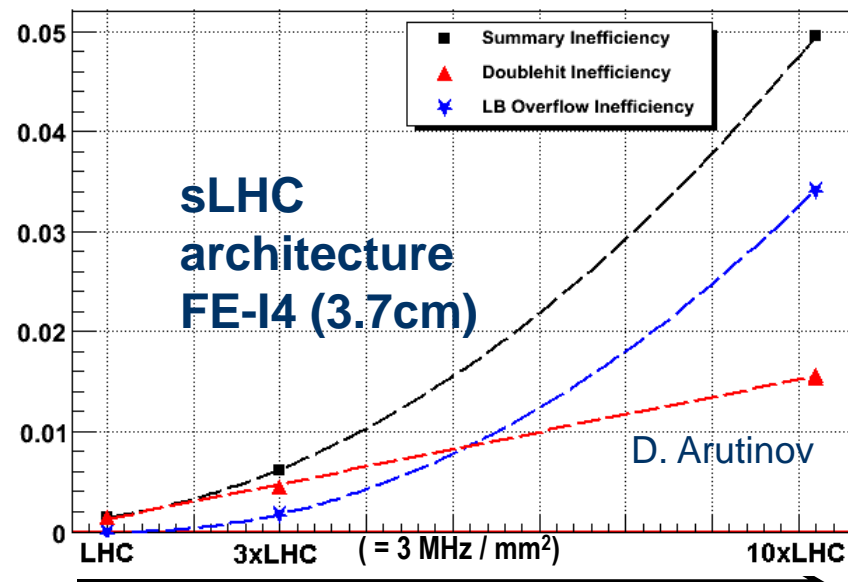
HL-LHC data rates & next ATLAS FE

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$1-\epsilon$

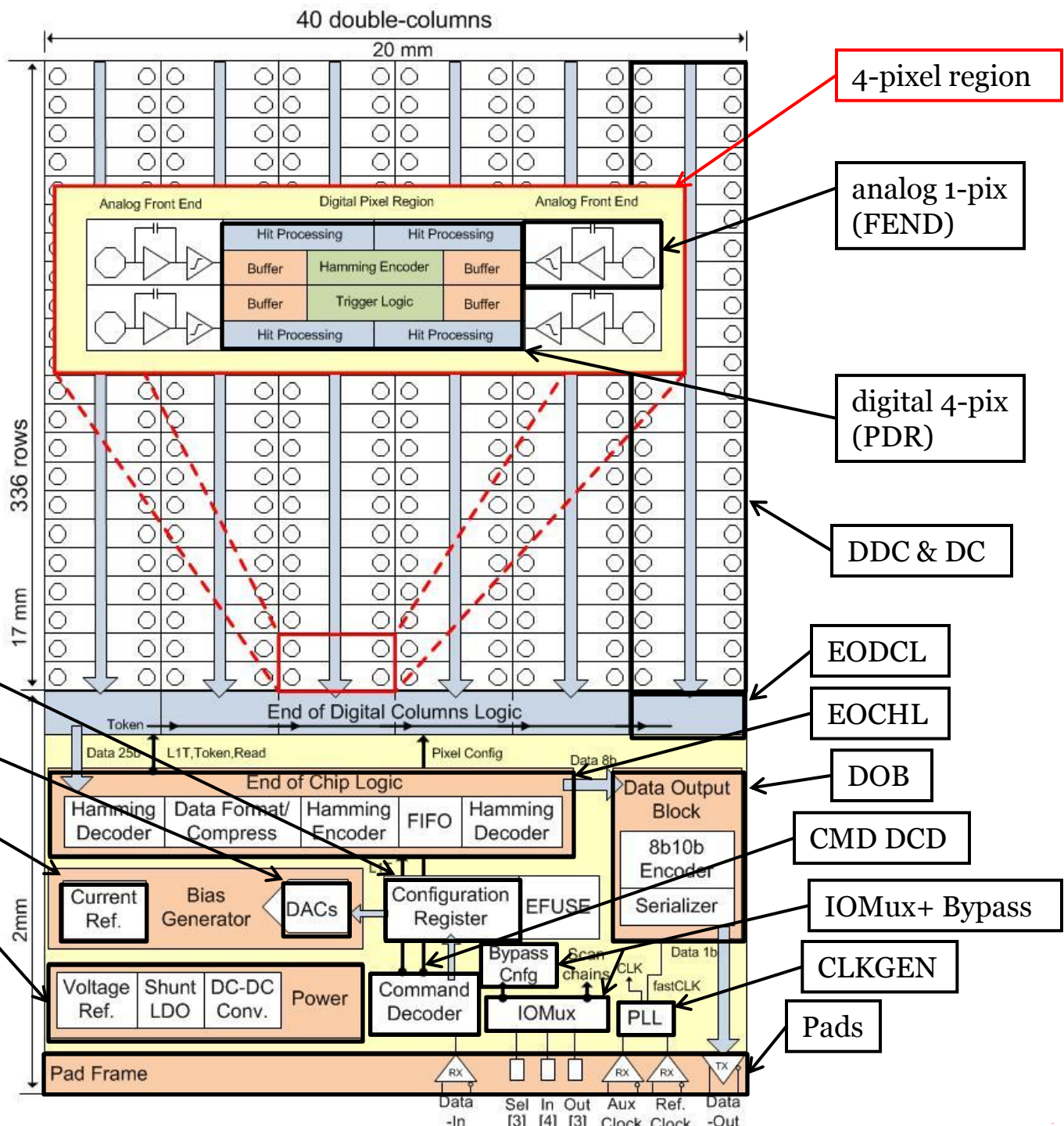


Bonn
 CPPM
 Genova
 LBNL
 NIKHEF

Overview

pixel array:
336×80 pixels

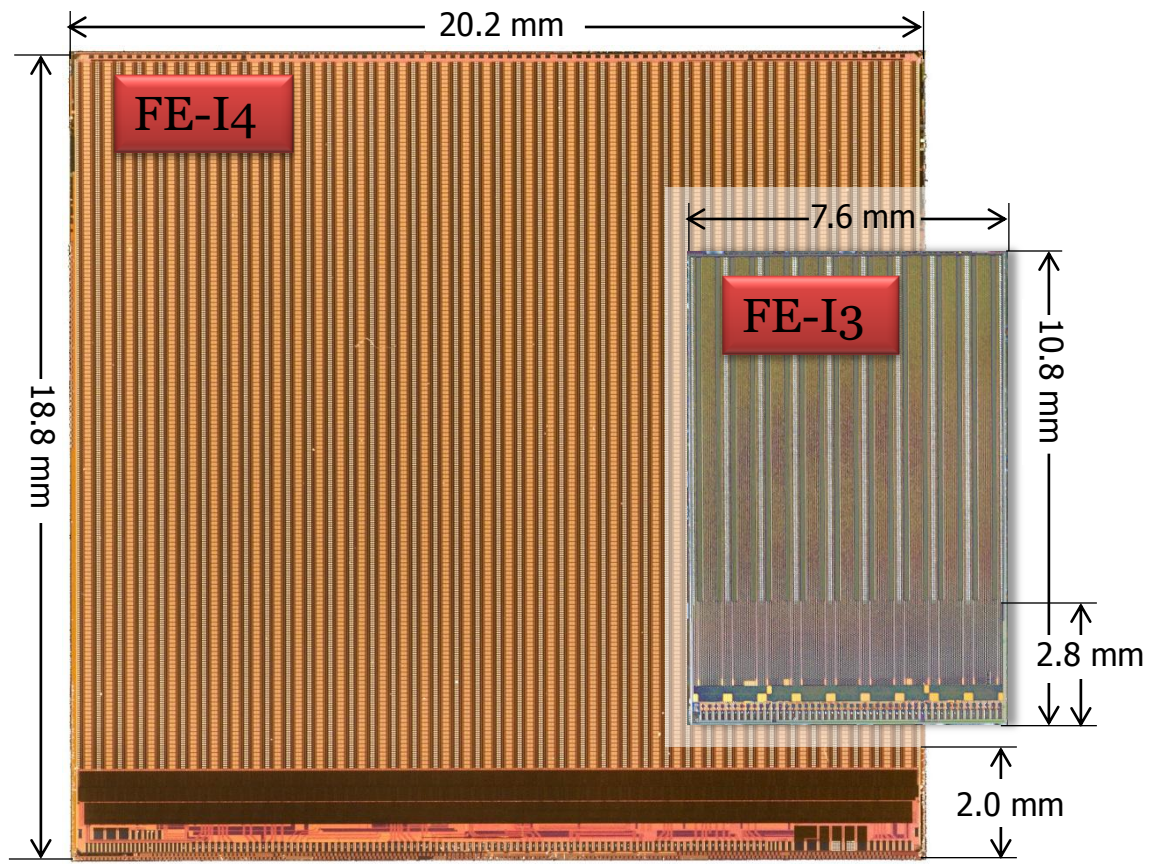
periphery



40 double-columns

20 mm

terminal region

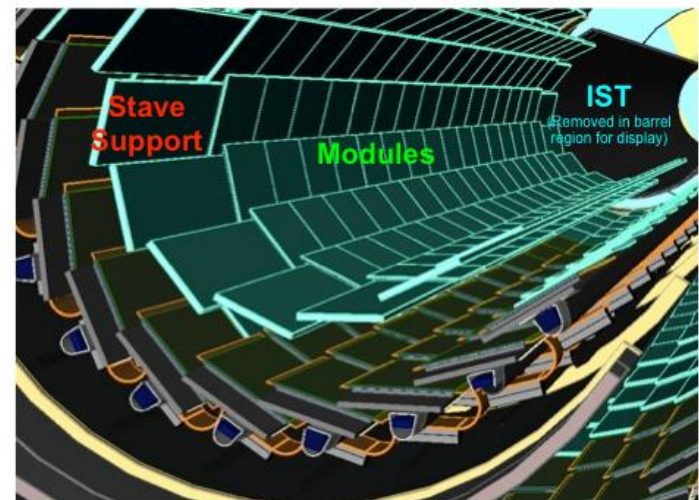
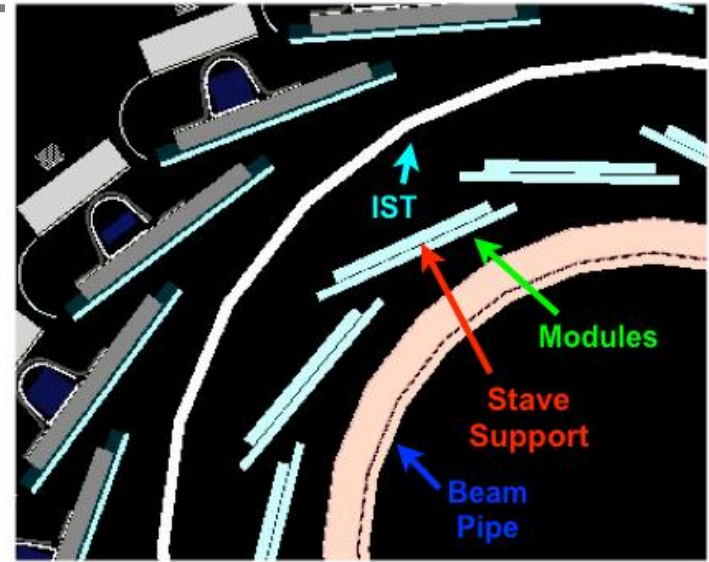


Data	Sel	In	Out	Aux	Ref.	Data
-In	[3]	[4]	[3]	Clock	Clock	-Out

The Insertable B-Layer

- Layout based on performance studies in G4 and available space:
 - ➔ smaller beam pipe ($R_{\min} = 26.5 \text{ mm}$)
 - ➔ reconstruction: 4th Pixel layer
 - ➔ IBL material adjusted to $1.5\% X_0$
 - ➔ smaller z pitch ($250 \mu\text{m}$)

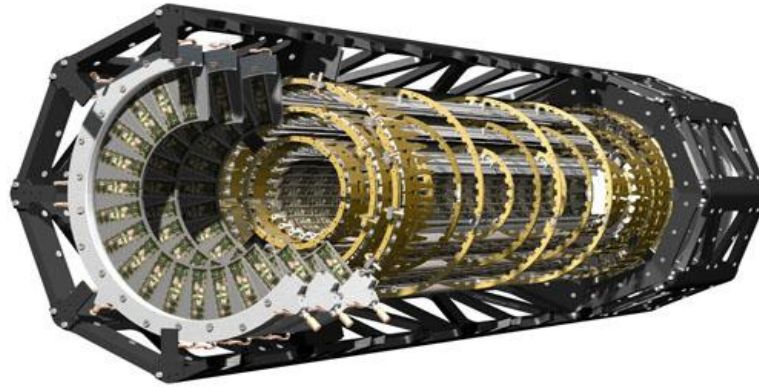
- ➔ Provide ATLAS with a 4 Layer Pixel Tracker from 2014 onwards.
- ➔ Maintain and improve physics performance (b-tagging vs. light jet rejection, vertexing) until HL-LHC.
- ➔ Provide redundancy in case of efficiency losses in other layers.
- ➔ Insertion of new pixel inside current pixel detector: Insertable B Layer IBL.
- ➔ IBL sensors at $\sim 34\text{mm}$ radius: 250 Mrad TID and $5 \times 10^{15} n_{\text{eq}}/\text{cm}^2 \text{ NIEL}$.
- ➔ Installation 2013!



Targets FE-I4: IBL & HL-LHC



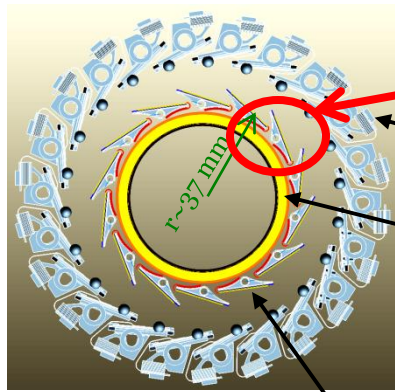
Present beam pipe & B-Layer



ATLAS Pixel Detector

3 barrel layers / 3 end-caps
 end-cap: $z \pm 49.5 / 58 / 65$ cm
 barrel: $r \sim 5.0 / 8.8 / 12.2$ cm

- Fast IBL ('13): inserted layer in current detector.



FE-I4B

Existing B-layer
 New beam pipe

IBL mounted on beam pipe

FE-I4C

NewPix

- Phase1 LHC / HL-LHC (>'17): 4-5 pixel layers, small radii / large(r) radii (note: Discussion on boundary pixel / short strips, ...).

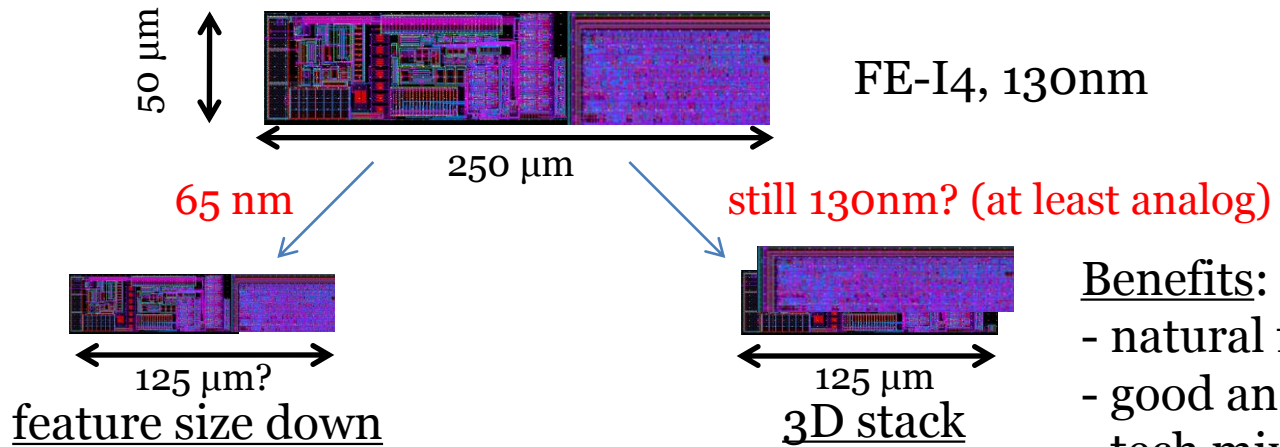
- All Silicon.
- Long Strips/ Short Strips / Pixels.
- Pixels:
 - 2 or 3 fixed layers at 'large' radii (large area at 16 / 20 / 25 cms?)
 - 2 removable layers at 'small' radii



Inner pixel layer at HL-LHC

- **Inefficient if FE-I4 like.**
- Need **higher rate** capability.
- Need **smaller, faster** pixel.
- Need **more memory** per pixel to handle high rate.
- Need new FE with **smaller pixel size and more space for digital pixel** → **smaller feature size** (e.g. 65nm) or **3D**.

IBL & outer pixel layers HL-LHC



Benefits:

- maturity.
- mainstream.

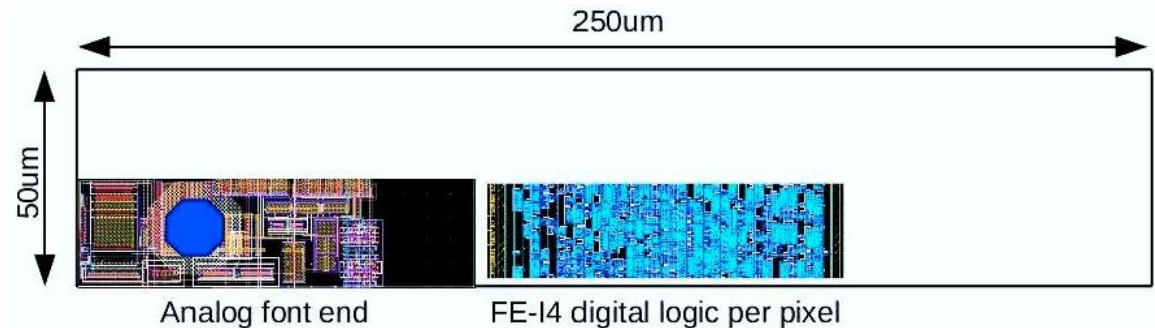
Benefits:

- natural fn split.
- good analog.
- tech mix.

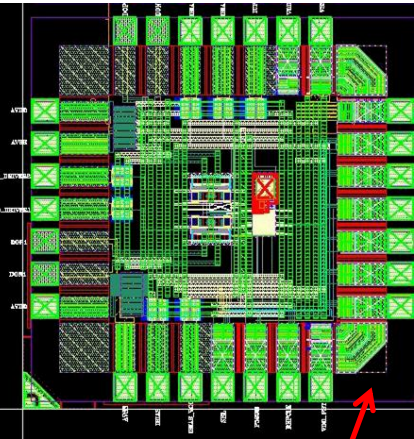
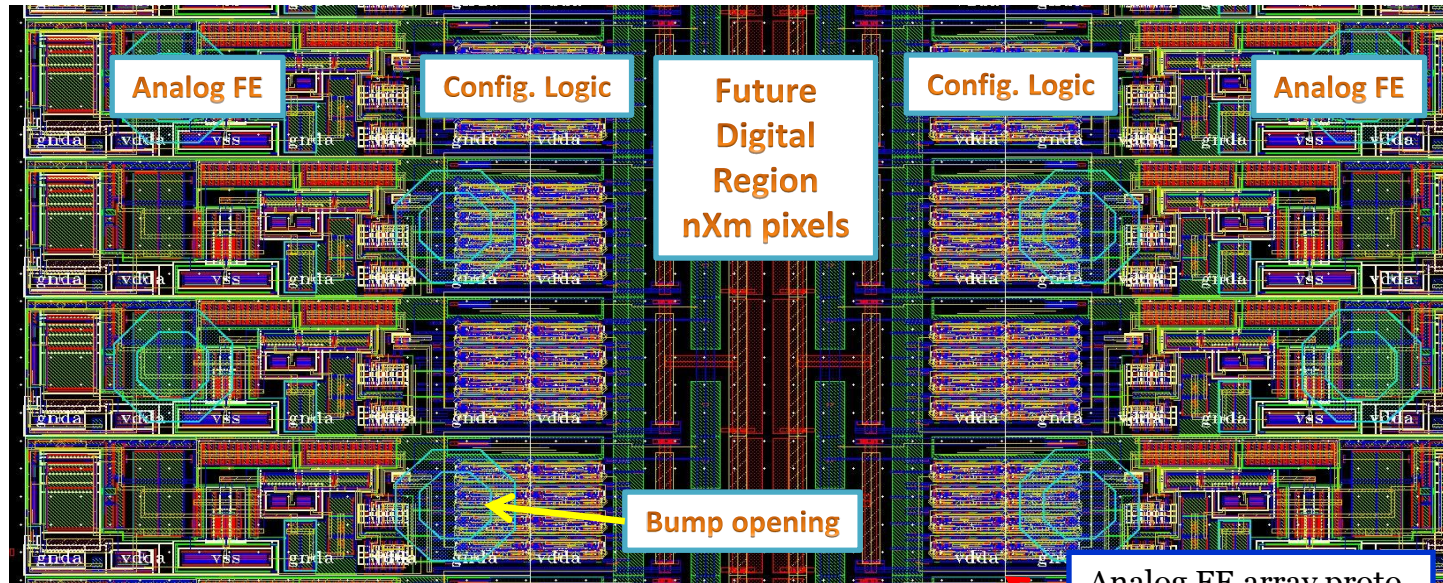
And make more clever pixels!

65nm CMOS effort

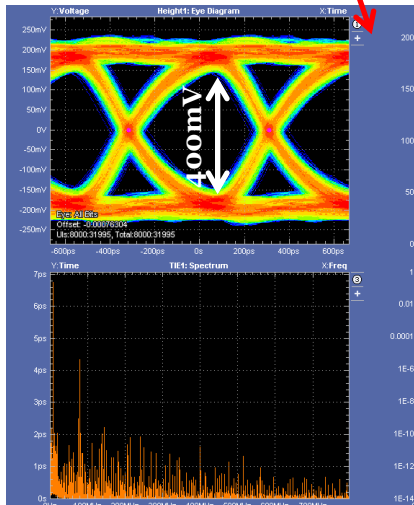
- Approx. **factor 4 area reduction** for digital circuits wrt 130nm.
- Conventional wisdom says not much gain for analog circuit (as needs employ more complex archi., move away from minimal).
 - Still transistor performance is not all the picture (capacitors, switches, interconnects do scale!)
 - Strategy then to reduce analog complexity, and do more on digital signal processing.
- **Prototyping for HL-LHC has started:** Array, prototype blocks – low power comparator, RAM, PLL (synergy with Depfet DHP digital IC design)-.



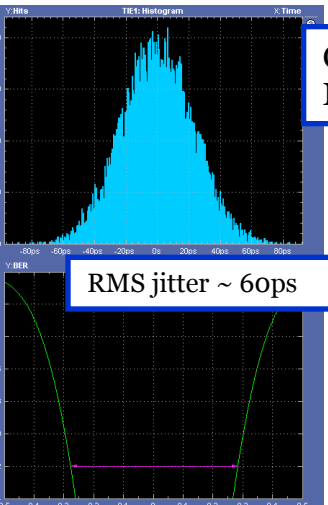
1st prototypes in 65nm



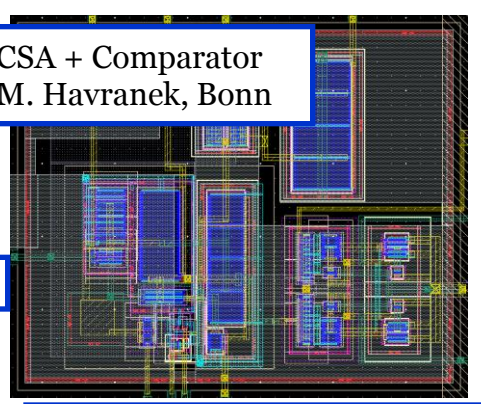
1.6 GHz PLL-PRBS-CML
T. Kishishita, Bonn



1.6 Gbps, PRBS, preamp on

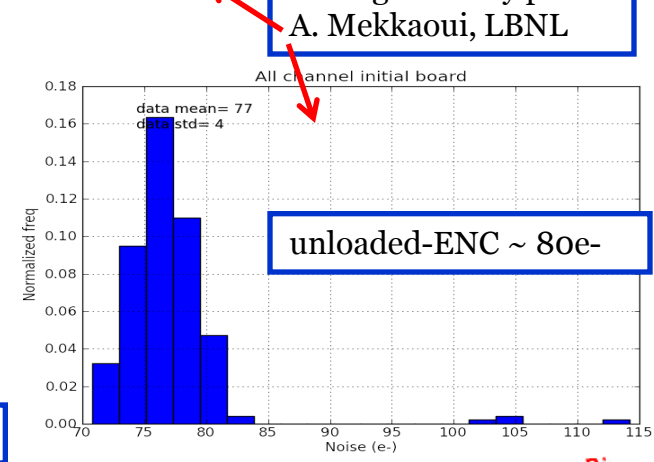


Carlton Barbero, Uni Bonn, 3D and NewPix, HHA Detektor WS 2012, Mar. 15th



CSA + Comparator
M. Havranek, Bonn

dyn. comp.: 2.4μW @40MHz



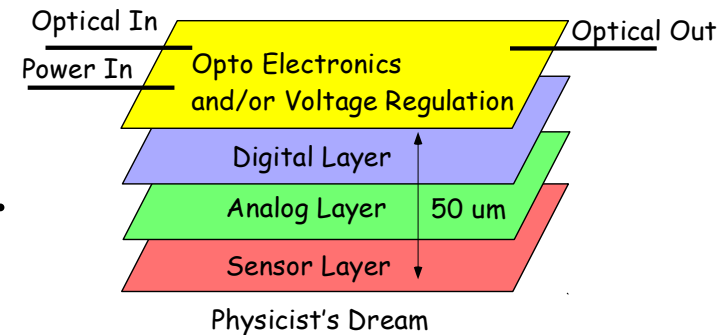
Analog FE array proto
A. Mekkaoui, LBNL

unloaded-ENC ~ 80e-



3D electronics: FE-TC4

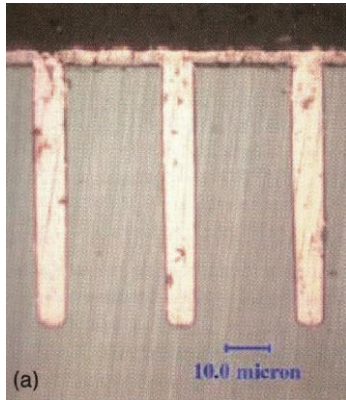
- Collaboration Bonn (Germany), CPPM (France), LBNL (USA).
- Goal: a $50 \times 125 \mu\text{m}^2$ 3D chip, with split analog and digital functionalities.
- Technology:
 - 130nm (restricted to 5 metals for now).
 - 3D process.
- Prototypes submitted in 2D, as technology test bench.
 - Good performance, good radiation tolerance.
- 3D analog + digital stack submitted. 1st prototypes back last year.



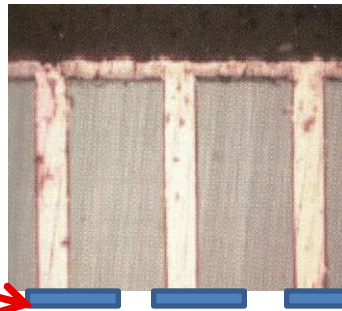
3D technology enablers

Metallization after thinning

Through silicon via

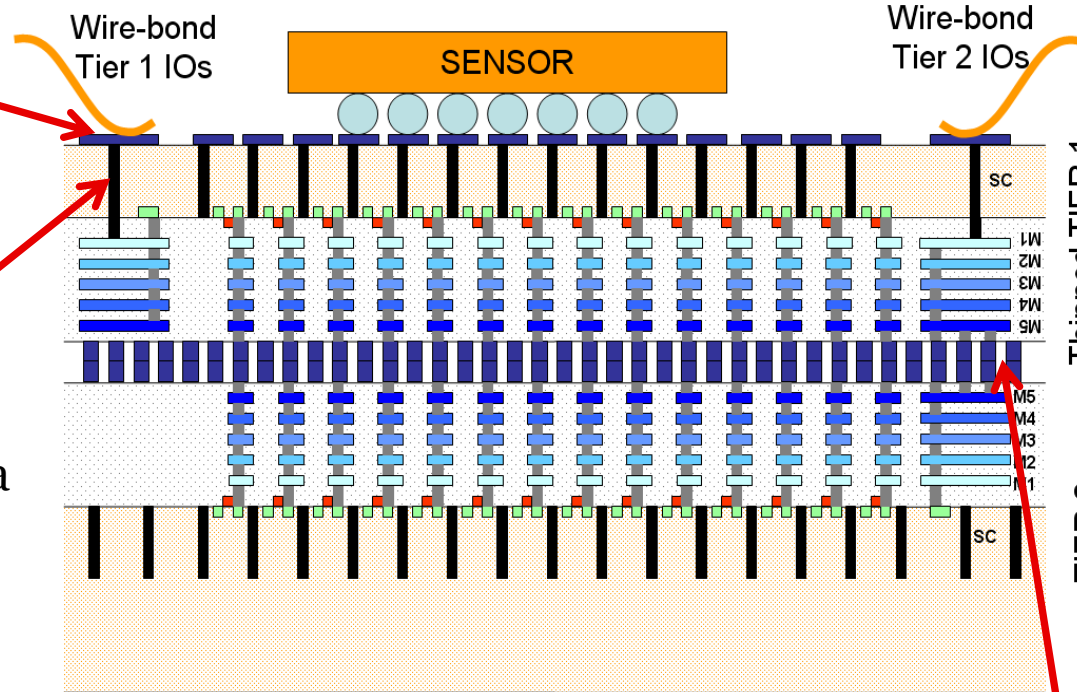
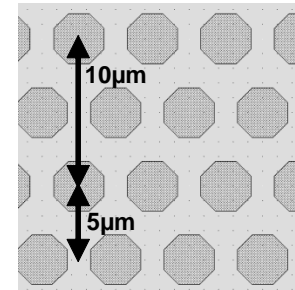


Via access after thinning



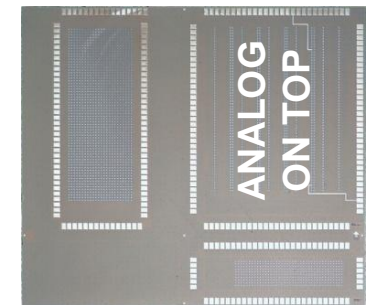
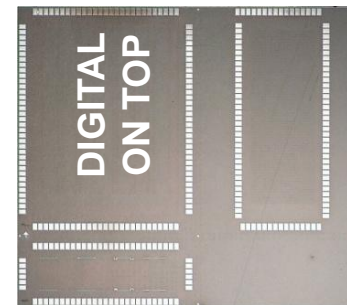
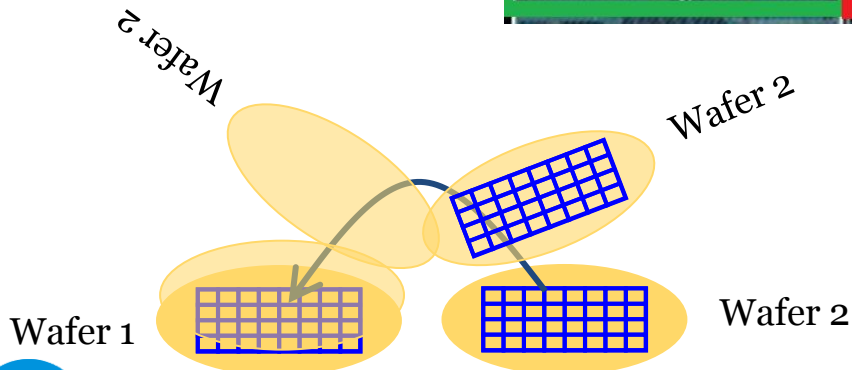
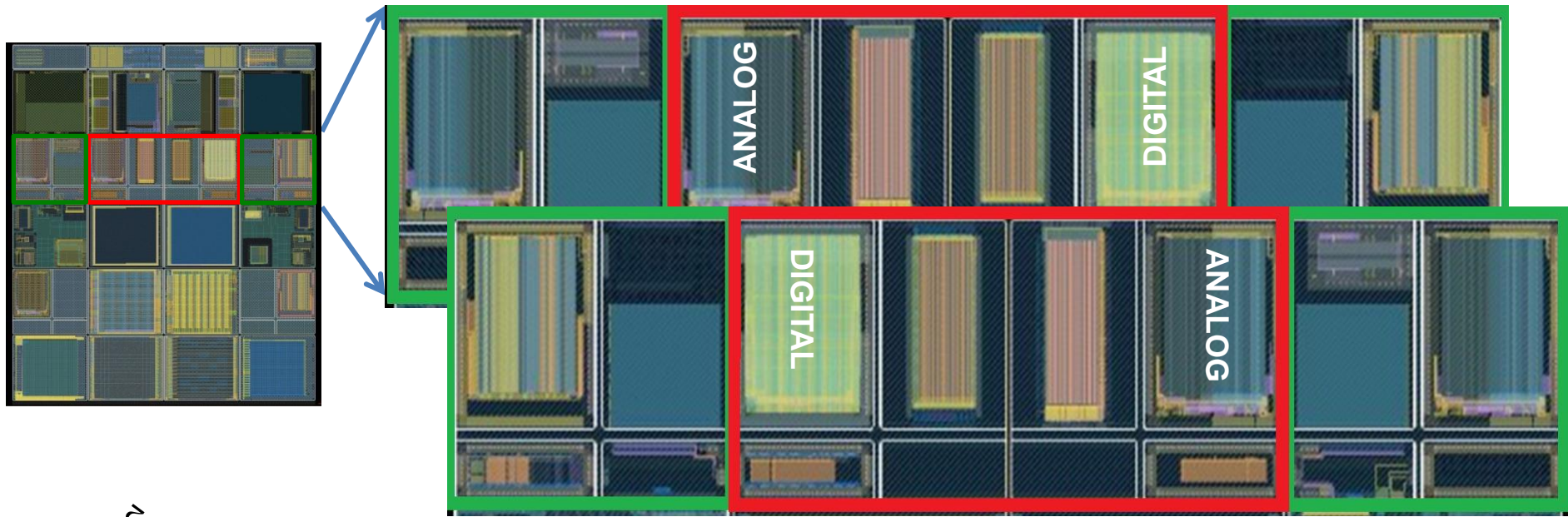
Metallization

Intertier bonding interface



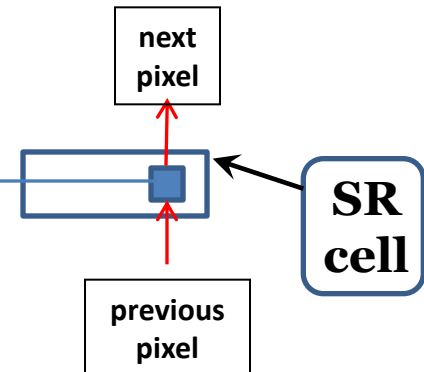
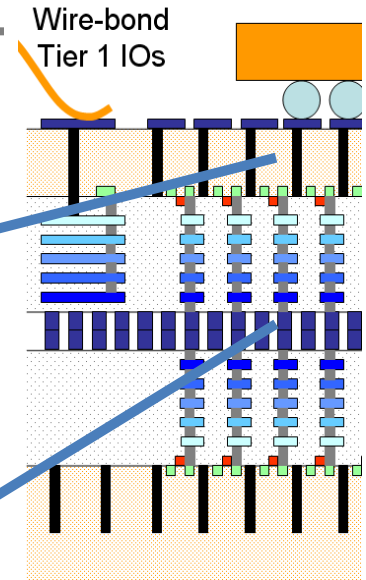
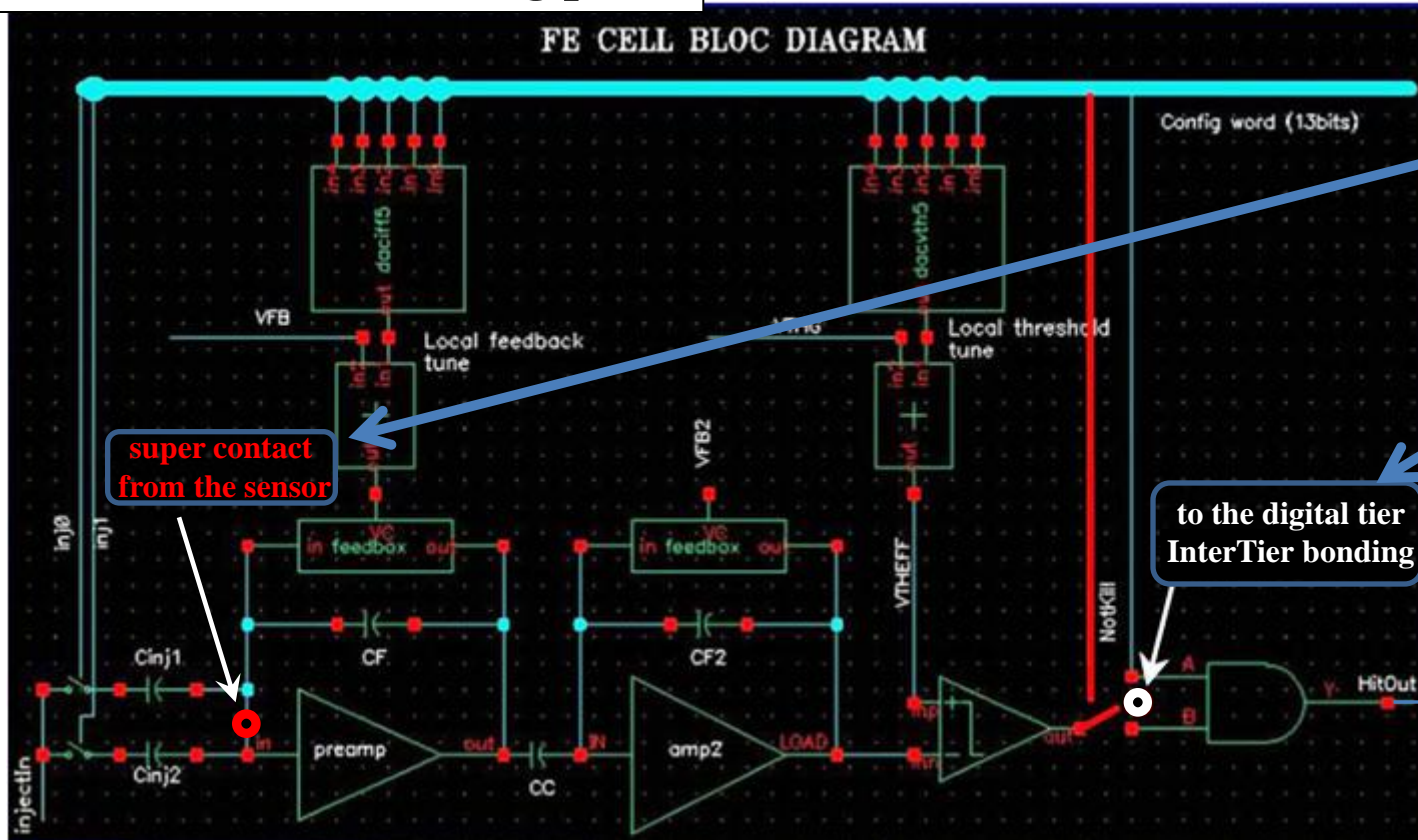
1st HEP 3D MPW

- FNAL led (participants from Canada, France, Germany, Italy, Poland, USA).



Analog Tier

Based on FE-I4 analog pixel



2 read-out mechanisms:

- Based on the analog tier shift register.
- Using the digital tier.

Digital Tier

Based on FE-I4 4-pixel region

- Simplified periphery: Control signals provided from outside

- Simple configuration through a shift register.

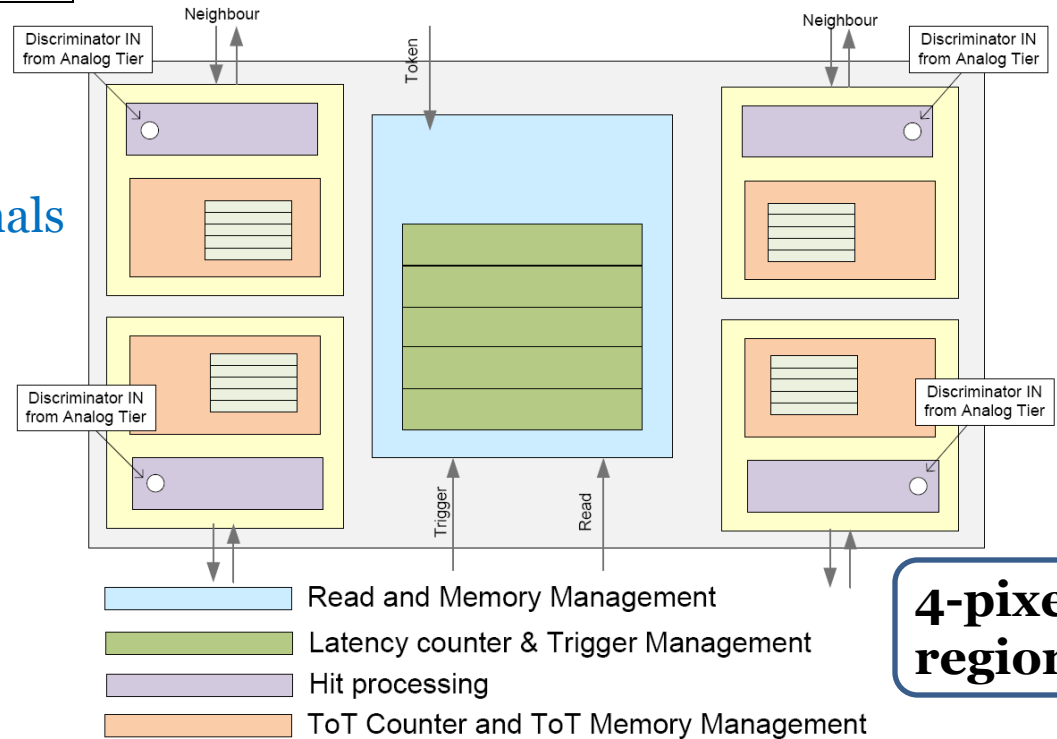
- 2 readout modes:

- simple readout using DC shift register for test purposes only.

- no ToT, read-out *whole pixel array*.

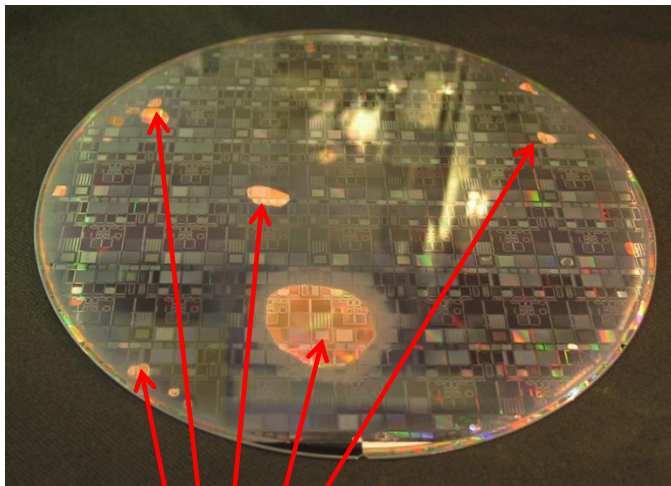
- regular readout similar to the full FE-I4.

- read-out *only triggered pixels, ToT information*.

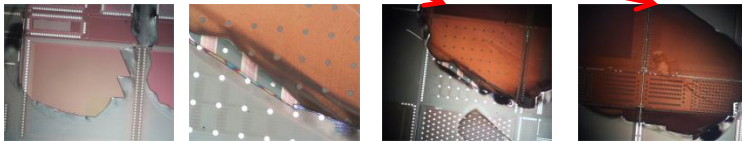


3D IC processing issues

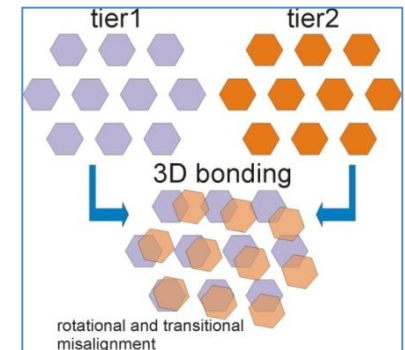
- > 30 single wafers produced , only 3 bonded wafer pair of poor quality accepted so far.



Damages on the wafer &
Close up photographs

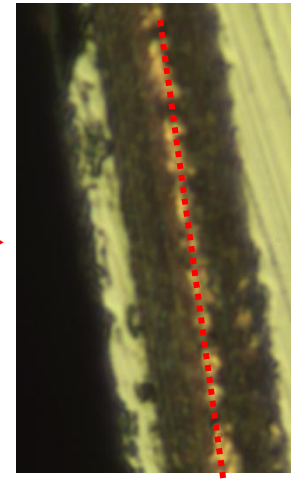
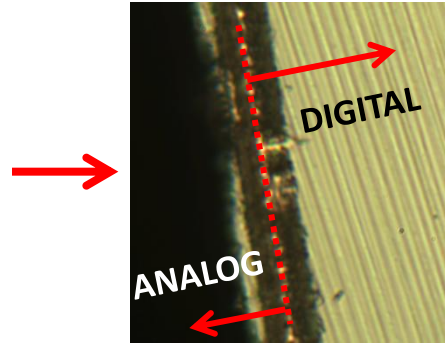
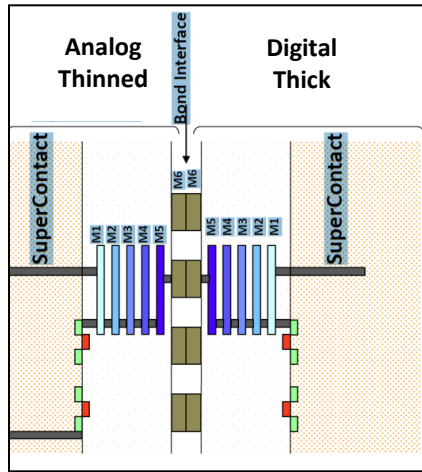


Bad electrical & mechanical connection due to misalignment of the tiers.

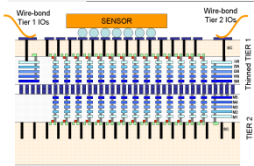


Bad mechanical connection between tiers lead to top tier removal during thinning process

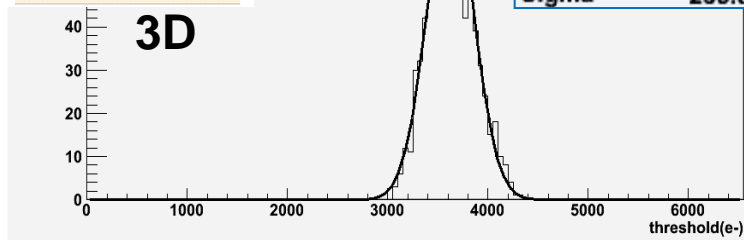
12 μm thinned down analog tier



Threshold

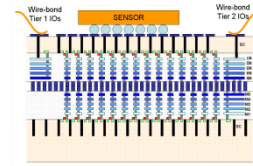


3D

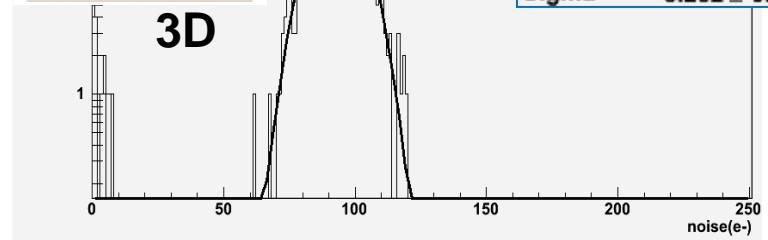


Entries	854
Mean	3630
χ^2 / ndf	20.54 / 23
Prob	0.6093
Constant	71.66 ± 3.14
Mean	3624 ± 8.5
Sigma	233.8 ± 6.7

Noise



3D



Entries	854
Mean	91.31
χ^2 / ndf	56.67 / 52
Prob	0.3049
Constant	38.76 ± 1.79
Mean	93.19 ± 0.30
Sigma	8.252 ± 0.254

**TSV drilled thinned down analog tier (12 μm !!!)
works with marginal noise increase.**

A perfect detector for HEP

Rad-hard

High hit rate

Large area

Monolithic

Intelligent pix

Low cost

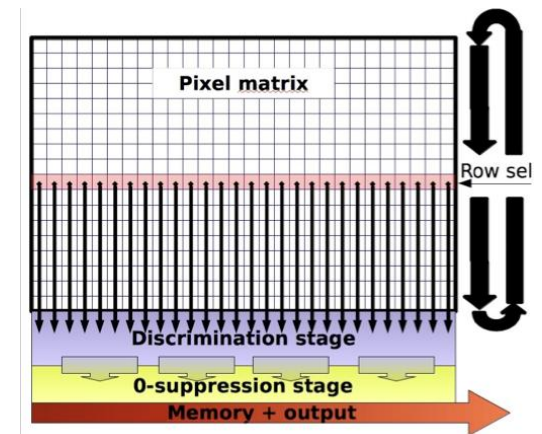
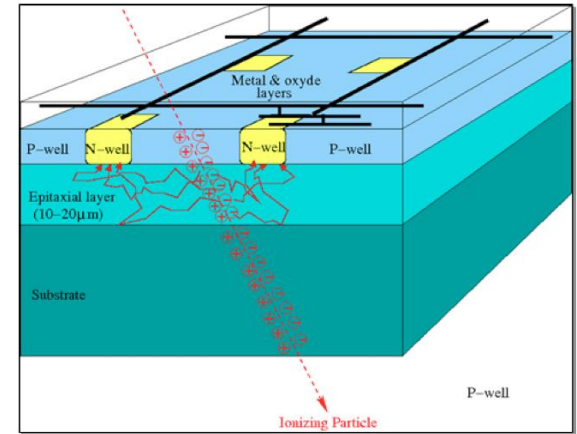
High resolution

Low noise

Low power

CMOS MAPS

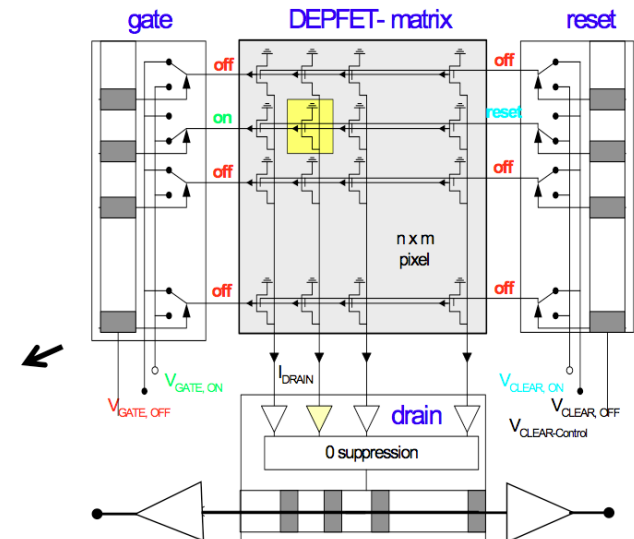
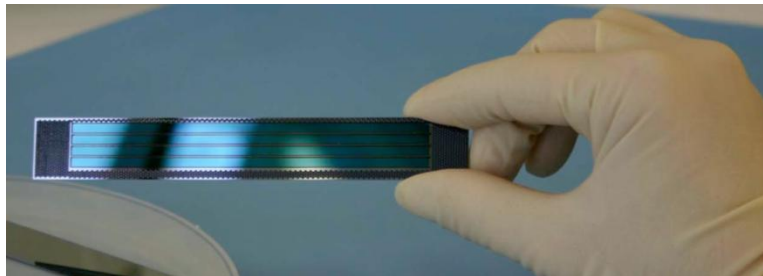
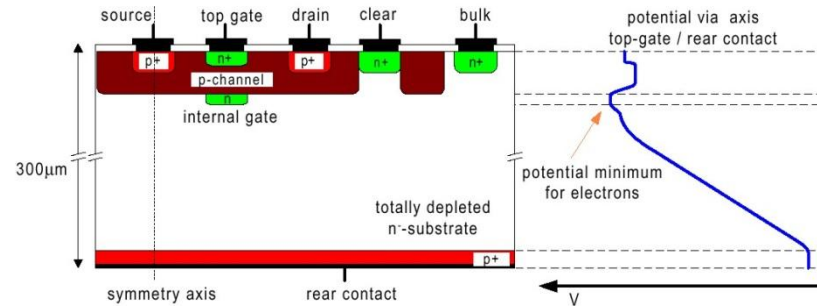
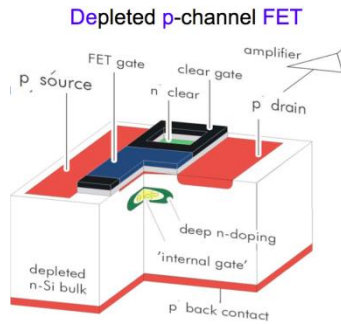
- standard CMOS process.
- no PMOS in-pixel.
- signal collection diffusion (speed).
- small signal (typ. $1000e^-$).
- small noise (typ. $20e^-$)
- small pixel size.
- not rad-hard.
- STAR pixel upgrade, EUDET telescopes



→ Suited for high precision, low rate, low rad.

Depfet

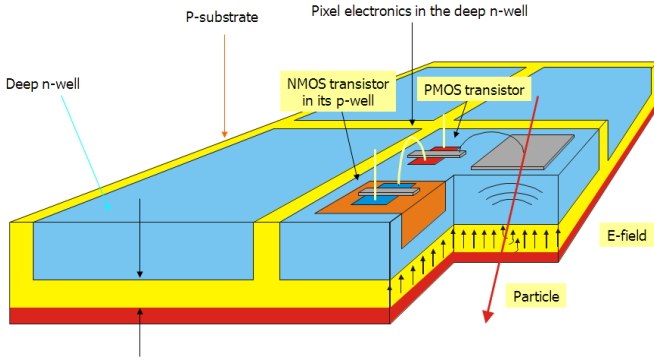
- Baseline for Belle II.
- pixel size $50 \times 50 \mu\text{m}^2$.
- SNR $\sim 20/1$
- rolling shutter, 100ns pro row.
- Thickness $\sim 75 \mu\text{m}$.



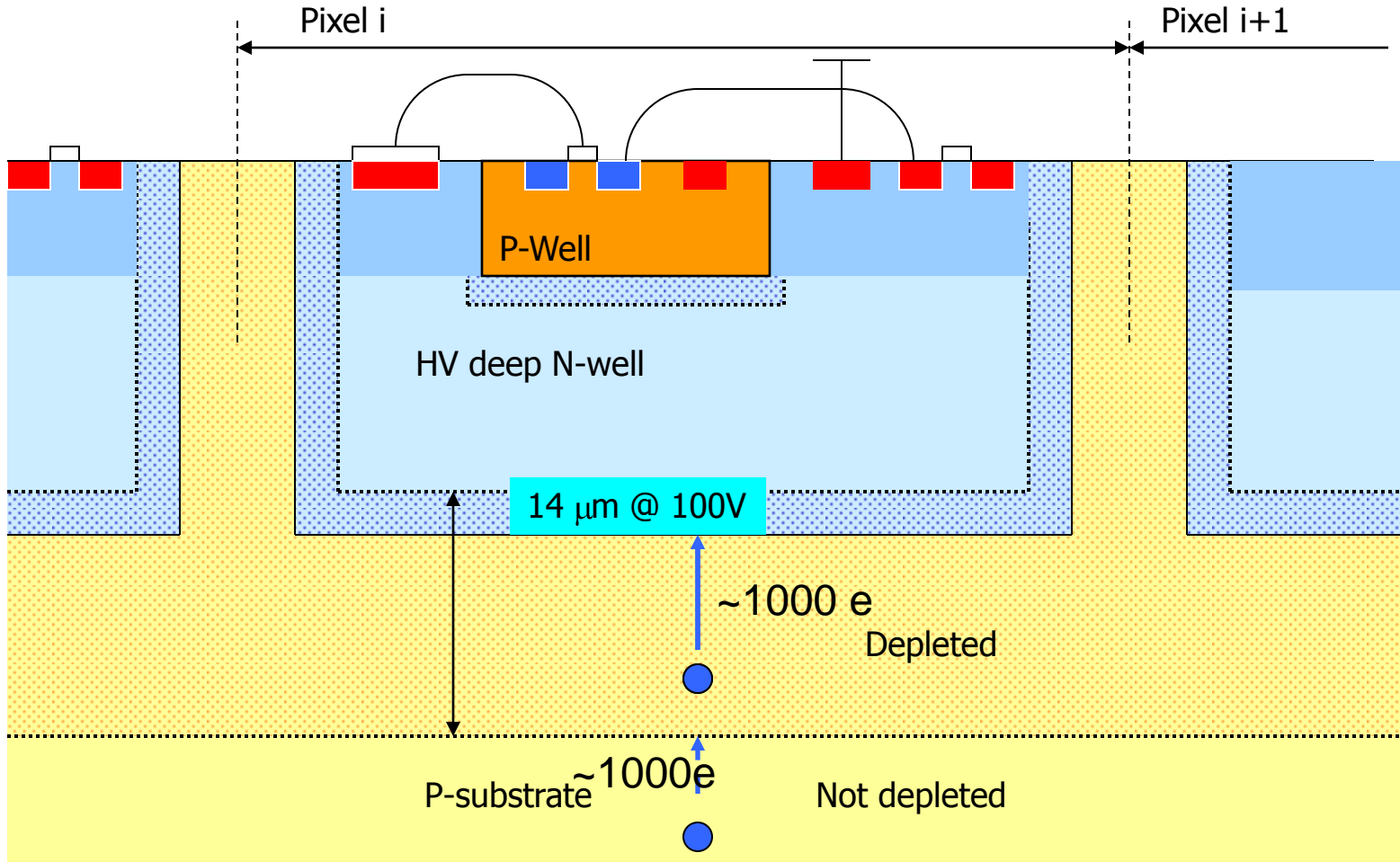
→ Suited for high precision, low rate, low rad.

HV-MAPS

Ivan Peric, Mannheim / Heidelberg



AMS 350nm → 180nm



Benefits and drawbacks

- Monolithic, **sensor + P/NMOS** .
- **Fast signal collection time** by drift.
- Charge collection @ surface → **thinning**.
- Low price (“standard CMOS”).
- **Tolerance to non-ionizing** radiation damage
(high drift speed, short drift path)
- **Tolerance to ionizing** radiation
 - (DSM, rad tolerant designs can be used)

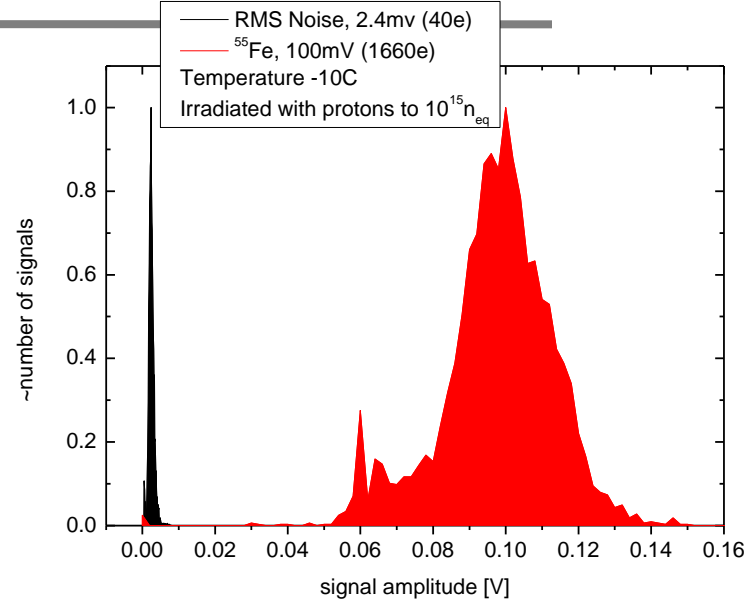
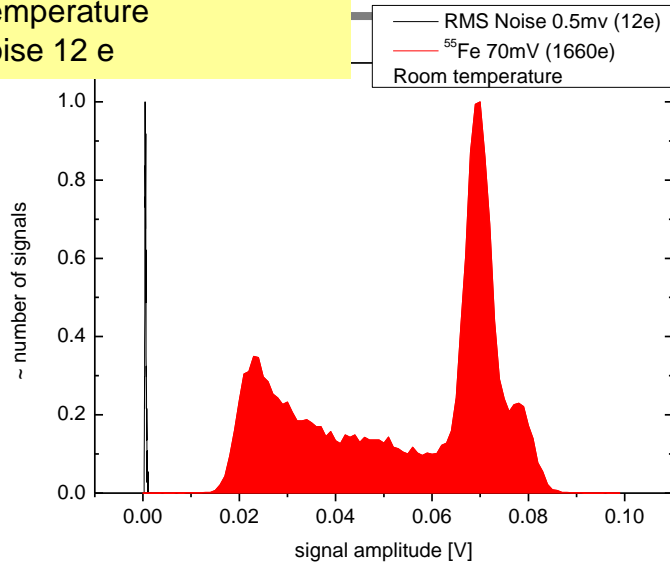
BUT:

- **PMOS and collection node share same bulk.**
- **Large size of collecting electrode.**
- **Not fully depleted.**

Rad and read

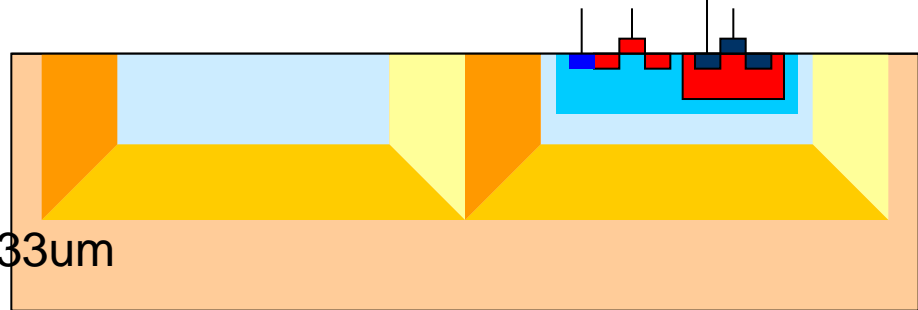
⁵⁵Fe spectrum, RMS noise
 Proton-irradiated $10^{15} n_{eq} / 300\text{Mrad}$
 -10C
 RMS Noise 40 e

⁵⁵Fe spectrum and RMS noise
 Not irradiated
 Room temperature
 RMS Noise 12 e



RO chip

Analog information



125um

33um

Read by capacitive coupled pixels?

- no bump-bond.
- increased resolution.
- commercial sensor techno.
- sensor thinning.
- bias < 60V.
- 100% fill factor.

125um

Conclusion

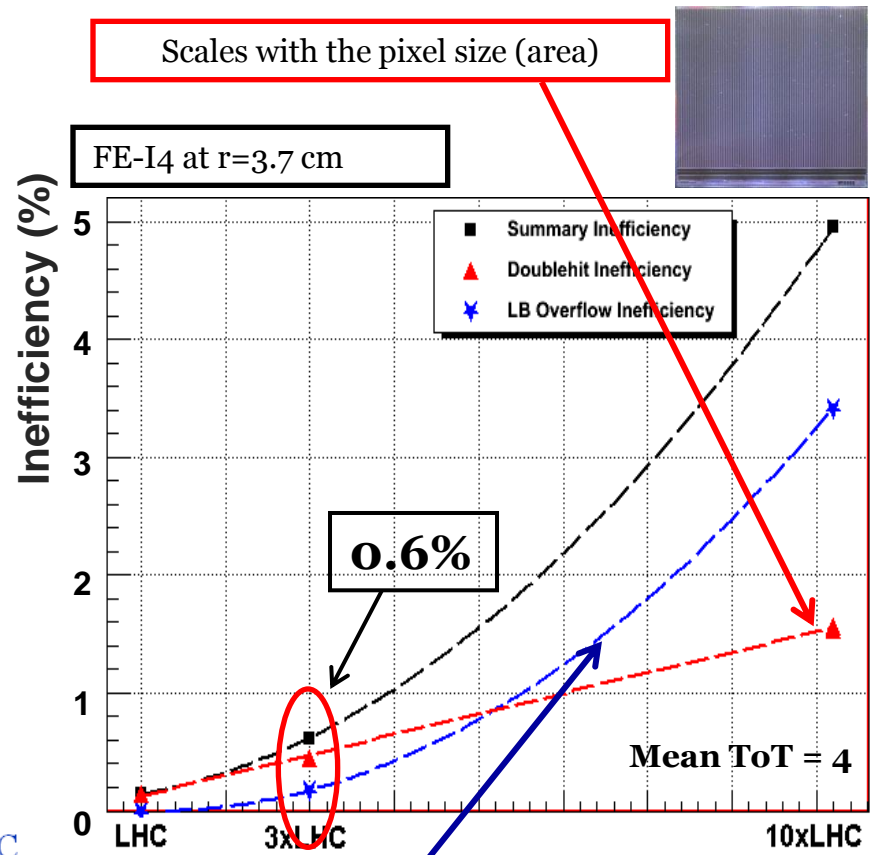
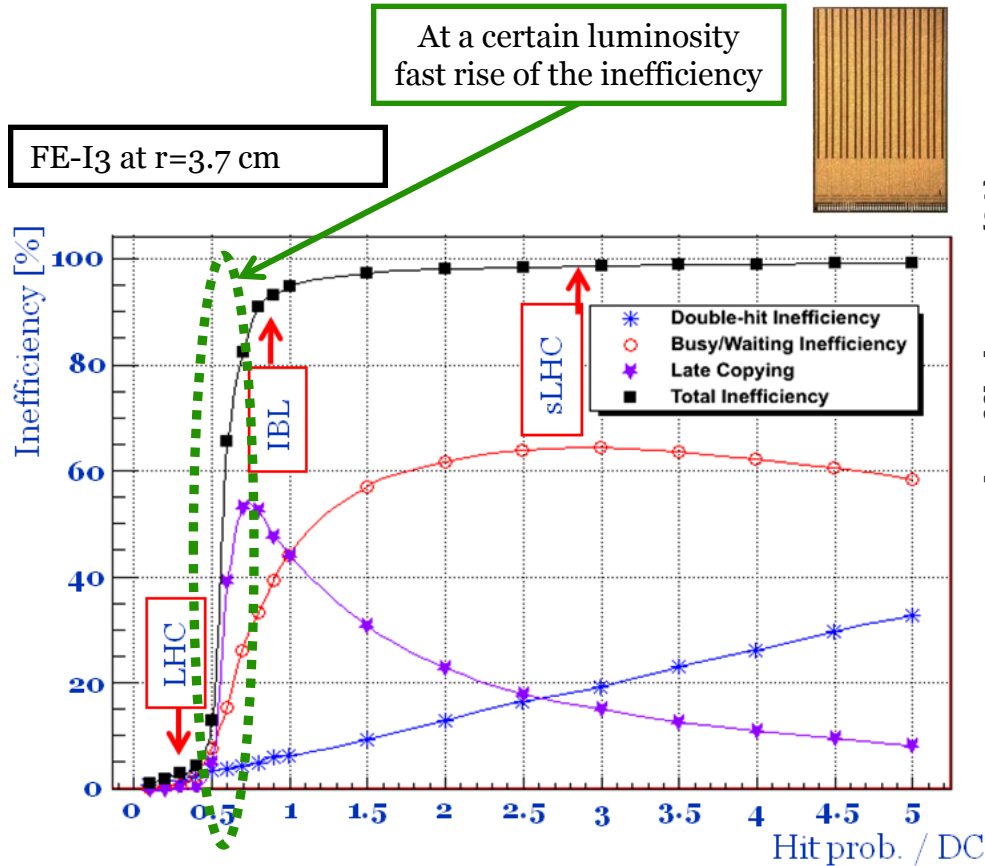
- LHC experiments now: the time of hybrid pixel technology.
- Still technologies used have aged, and hybrid pixel can benefit now from smaller feature size on FE side.
- But **new technologies might be game-changer for HEP**:
 - **3D** integration.
 - **Monolithic** concepts.
- **Keep an eye on new technologies** (new HV technology options which could solve HV-MAPS issues, use of HR wafers → 3 key words: **integration, isolation, depletion**).
- Not covered:
 - CMS upgrade efforts. R. Horisberger's talk
 - SoI developments, μ -pattern gas avalanche detector...

time well your efforts wrt process maturity!

Backup

BACKUP

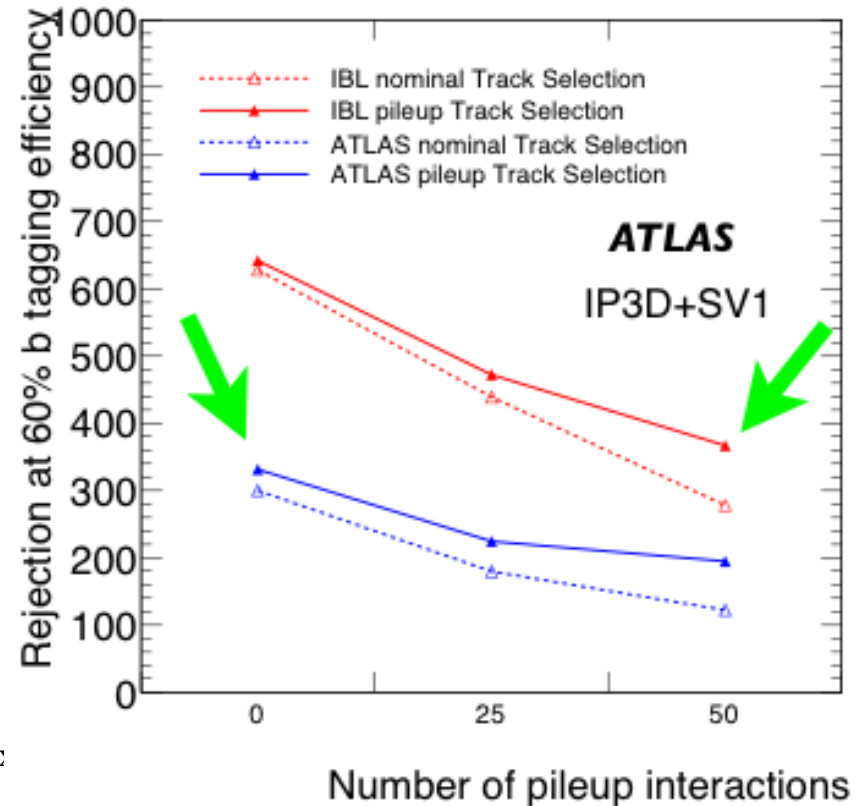
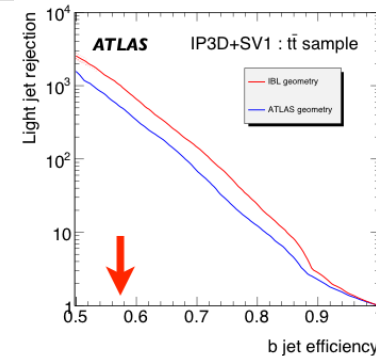
Hit rate



Can be kept low by storing more hits locally. Bigger memory size

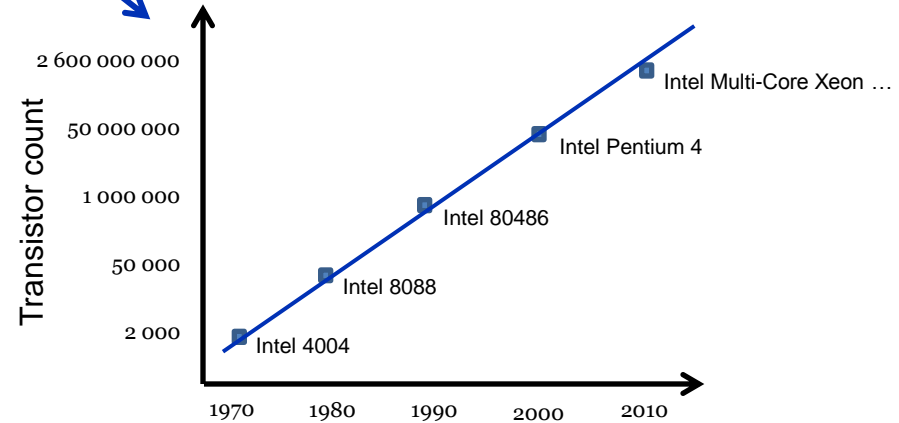
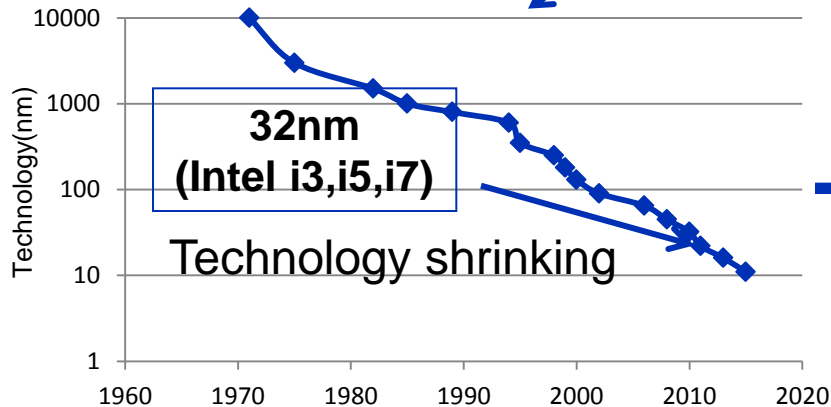
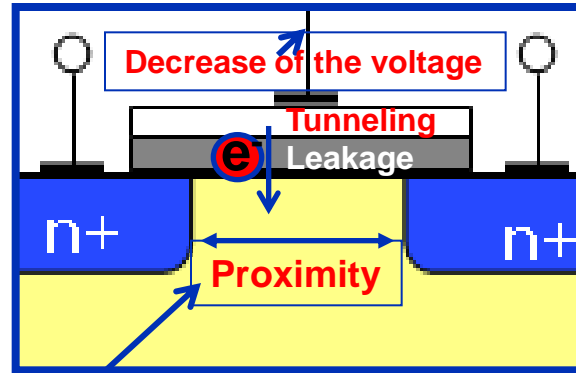
B-tagging with IBL

- Look at light-jet rejection at 60% b-tagging efficiency at different pile-up conditions:
- Rejection significantly increases with IBL
- “Restores” rejection for high pile-up events:
 - rejection at high pileup as good or better at current ATLAS without pileup
- Clear benefit from 4th layer
- The 4th Layer also provides redundancy against efficiency losses in other layers



Chips and Transistors

- Nowadays chips contain millions of transistors.

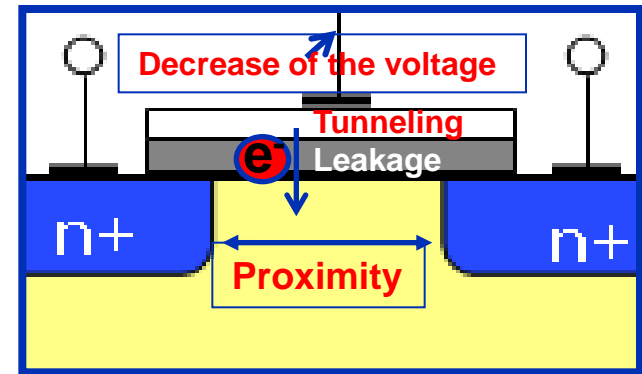


- Smaller transistors → More transistors per unit area → More functionality
- But smaller transistor size → new issues (smaller distance between “source” and “drain”, thin gates, Smaller gate voltage, tunneling effect and leakages, higher doping profile)

Limitations of scaling down

- Problems with feature size decreasing

- New issues @ transistor level
- Increase of interconnection density :
 - parasitic RC delays
 - parasitic inductances
 - increases heat dissipation
 - power consumption
 - noise coupling.

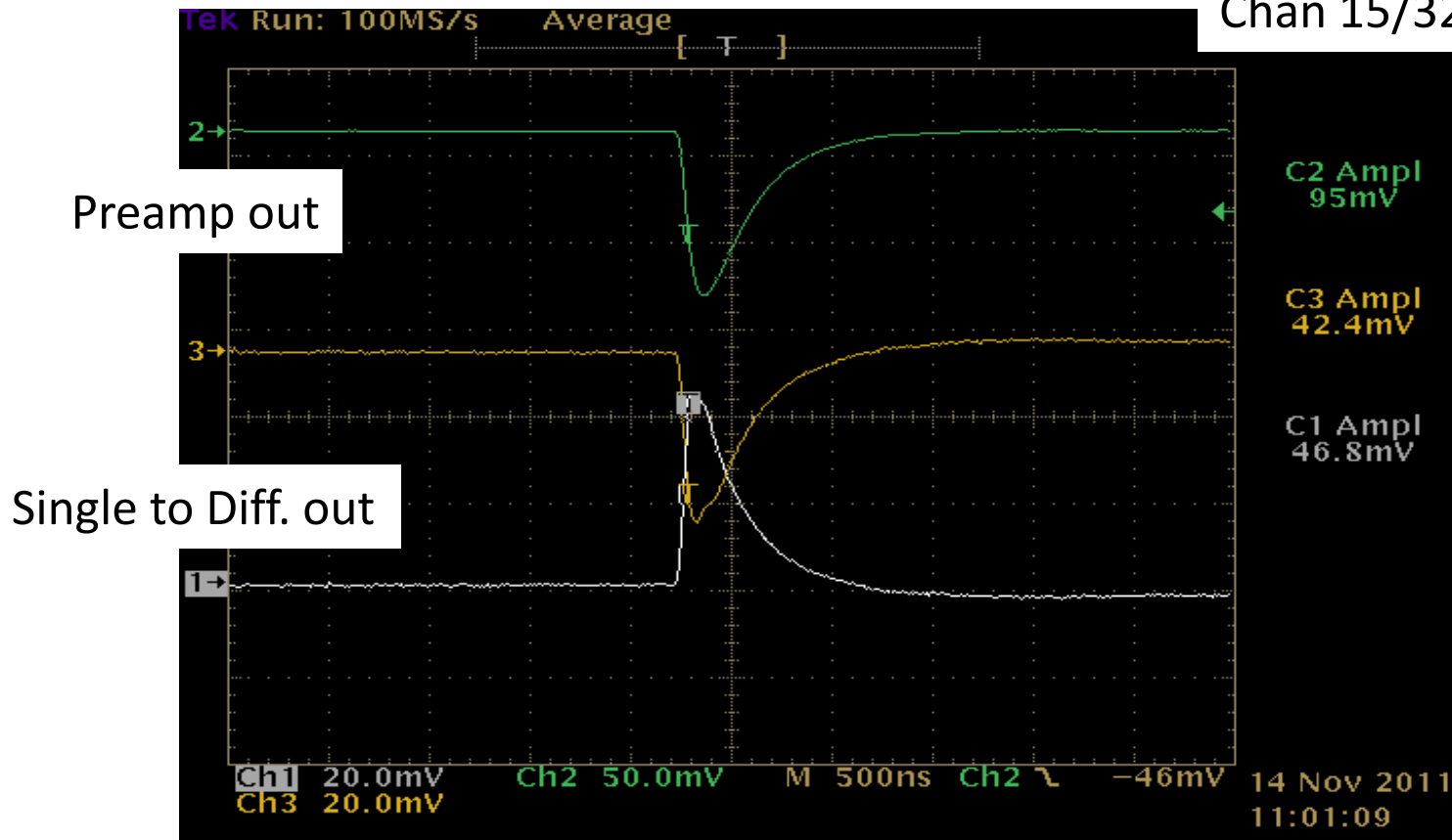


Wiring crisis

- Even if the above limitations will be circumvented mixed signal designs could suffer from the small feature size: when for the digital part this would be a natural choice, “designers’ conventional wisdom” → analog performance could degrade due to small transistor size.
- 3D packaging/integration could help
 - Possible solution could be to **break the IC circuit into several layers, and stack them on top of each other:**
 - More transistors per unit area without decreasing feature size.
 - Interconnect vertically. Shorter distance.
 - Different technologies for different layers.
 - Compact modules integration the sensor as well

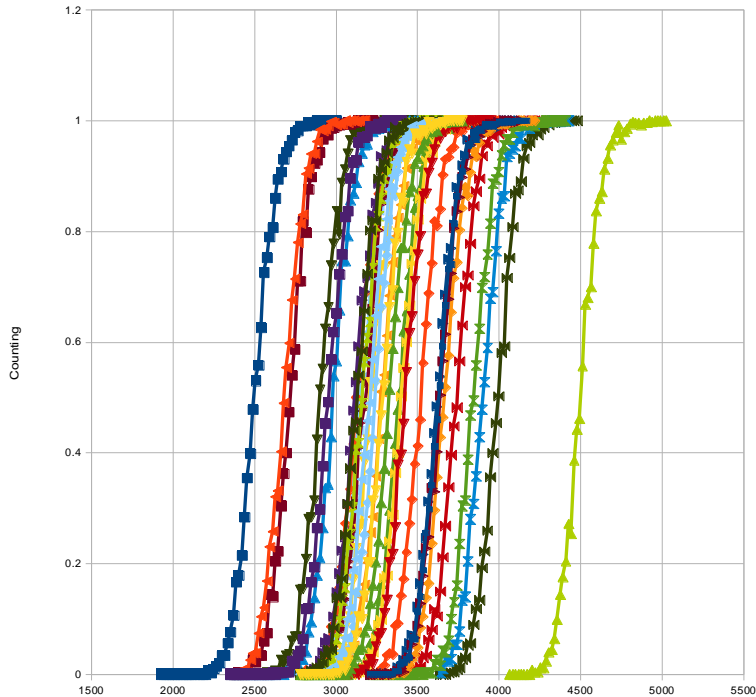
65nm array test results

Chan 15/32 Qin: 2ke

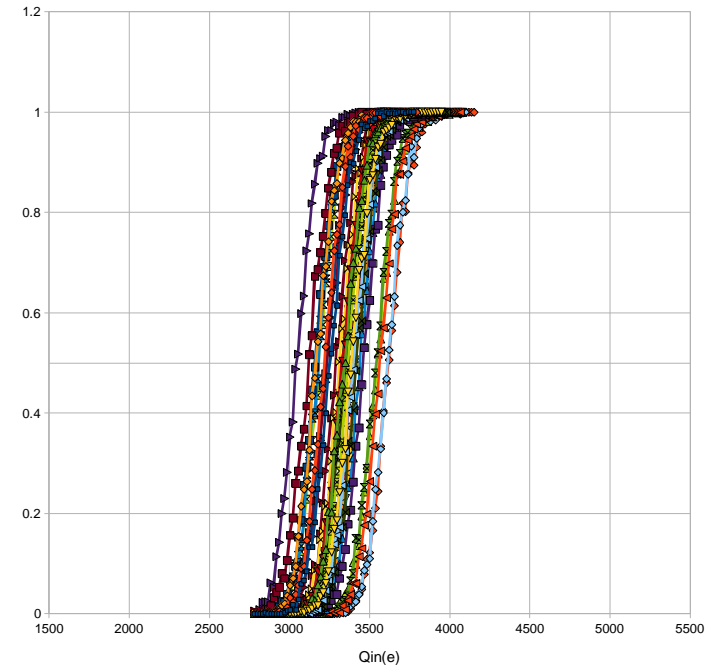


- Chip found to work as expected!
- VDD=1.2V
- I= 5 μ A per pixel (can be as low as 2 μ A)

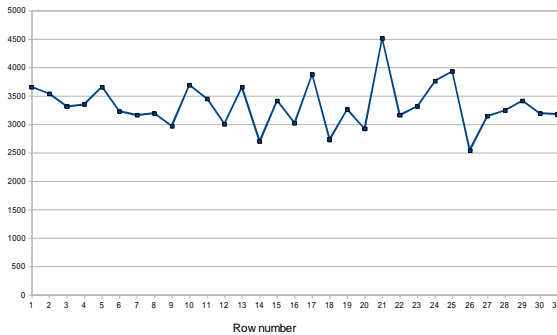
65nm, threshold adjustment



*COUNTS FOR COL , ROW: 12 , 1
 *COUNTS FOR COL , ROW: 12 , 3
 *COUNTS FOR COL , ROW: 12 , 4
 *COUNTS FOR COL , ROW: 12 , 5
 *COUNTS FOR COL , ROW: 12 , 6
 *COUNTS FOR COL , ROW: 12 , 7
 *COUNTS FOR COL , ROW: 12 , 8
 *COUNTS FOR COL , ROW: 12 , 9
 *COUNTS FOR COL , ROW: 12 , 10
 *COUNTS FOR COL , ROW: 12 , 11
 *COUNTS FOR COL , ROW: 12 , 12
 *COUNTS FOR COL , ROW: 12 , 13
 *COUNTS FOR COL , ROW: 12 , 14
 *COUNTS FOR COL , ROW: 12 , 15
 *COUNTS FOR COL , ROW: 12 , 17
 *COUNTS FOR COL , ROW: 12 , 18
 *COUNTS FOR COL , ROW: 12 , 19
 *COUNTS FOR COL , ROW: 12 , 20
 *COUNTS FOR COL , ROW: 12 , 21
 *COUNTS FOR COL , ROW: 12 , 22
 *COUNTS FOR COL , ROW: 12 , 23
 *COUNTS FOR COL , ROW: 12 , 24
 *COUNTS FOR COL , ROW: 12 , 25
 *COUNTS FOR COL , ROW: 12 , 26
 *COUNTS FOR COL , ROW: 12 , 27
 *COUNTS FOR COL , ROW: 12 , 28
 *COUNTS FOR COL , ROW: 12 , 29
 *COUNTS FOR COL , ROW: 12 , 30
 *COUNTS FOR COL , ROW: 12 , 31
 *COUNTS FOR COL , ROW: 12 , 32



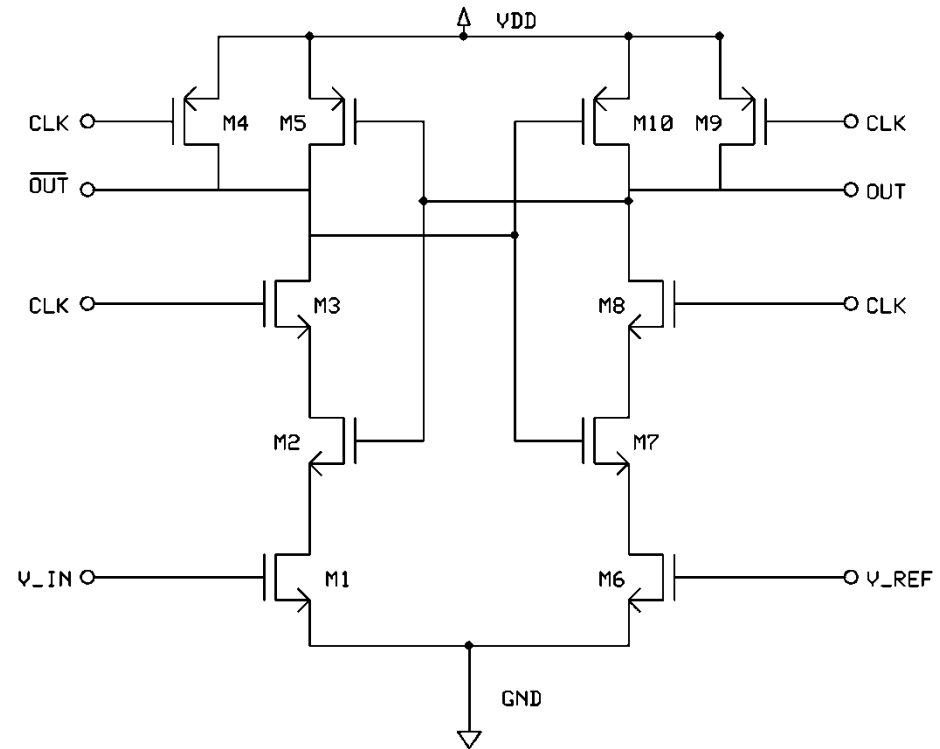
Threshold for the column 12



- Mean value : 3350 e-
- RMS value : 140 e-
- Peak to peak value : 560 e-

Dynamic comparator

- Motivation: reduce power consumption
 - comparator in FE-I4 has static power consumption of $5.6 \mu\text{W}$
- Benefits of dynamic comparator:
 - high speed
 - nearly zero static power consumption
 - low voltage operation
 - rail to rail output
 - small chip area
- Drawbacks:
 - sensitivity to correct layout (symmetry)
 - sensitivity to symmetric load

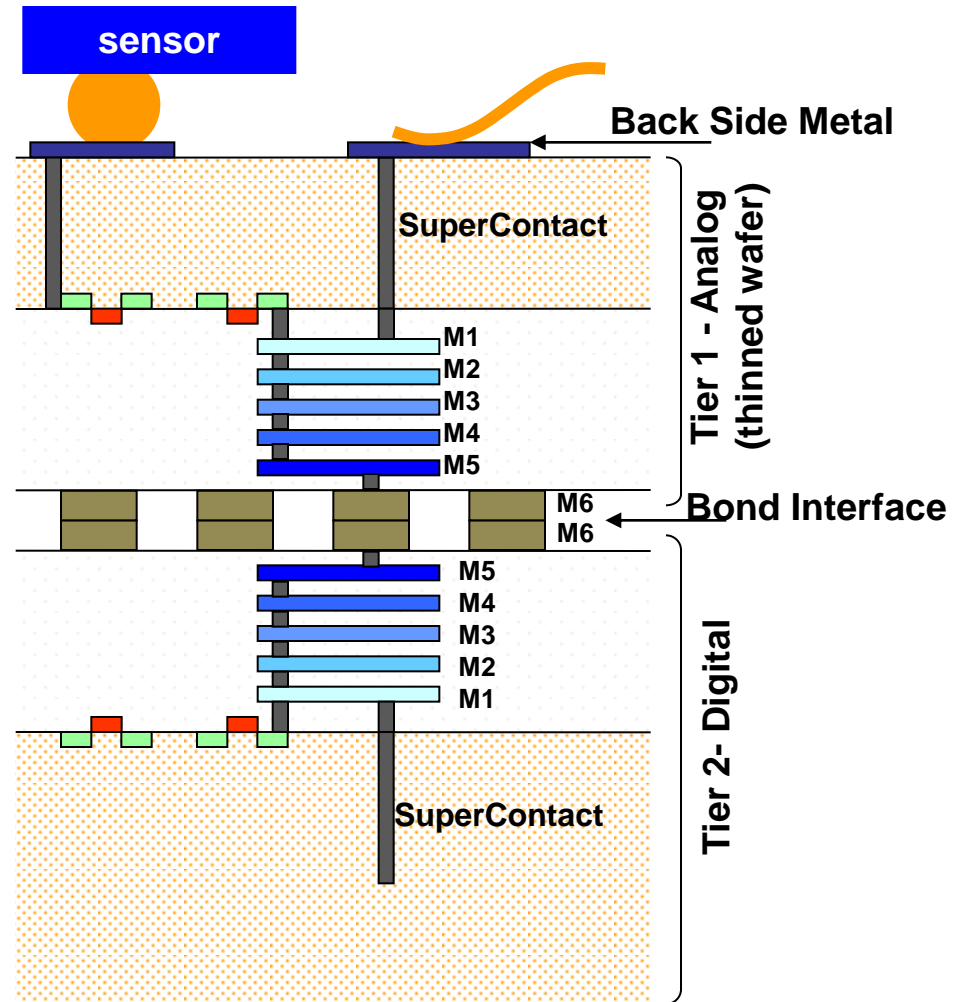


Dynamic comparator – post-layout simulation data

- Static power: 3.18 pW
- Power at 40 MHz: 2.33 μ W (digital buffer as a load)
- CLK-OUT delay: < 1 ns
- Voltage offset:
 - 1.2 mV at $V_{ref} = 500$ mV
 - 12.1 mV at $V_{ref} = 800$ mV
 - 28.2 mV at $V_{ref} = 1000$ mV
- Useful voltage range: 300 mV – 1V
 - low limit is given by decision time < 10 ns
 - high limit is given by |voltage offset| < 28 mV

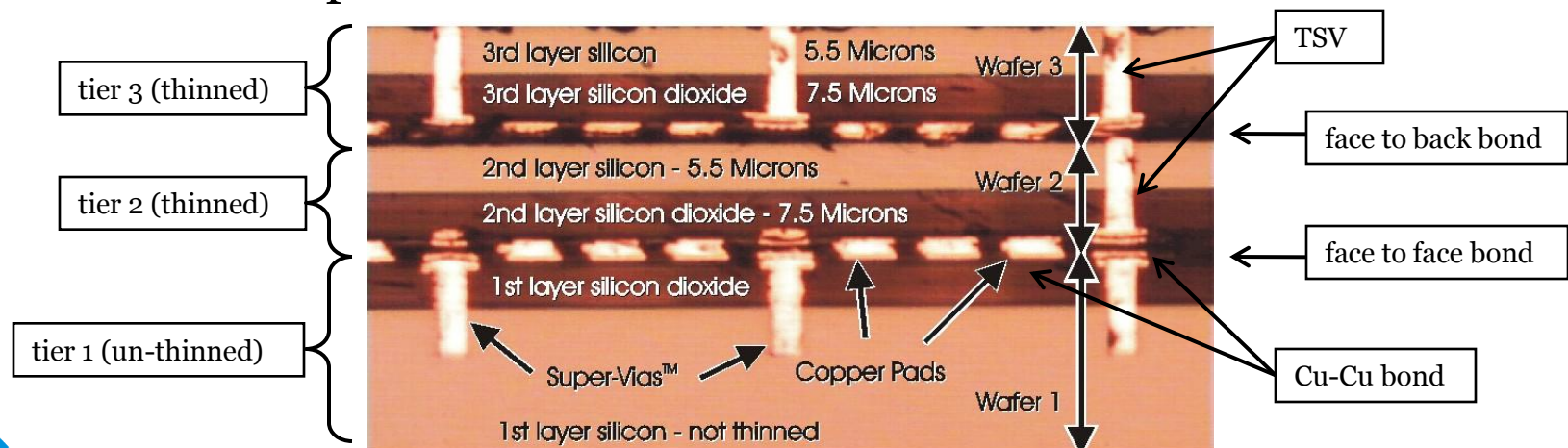
3D TC stack

- Tier 1 is thinned.
- IO of each tier are independent, each tier can be tested stand-alone.
- Digital tier comes in 2 versions.
- In the future, **sensor can possibly be integrated** tier on top of analog tier → when (/If?) processing mature, very flexible technology with **each tier adapted to your application**



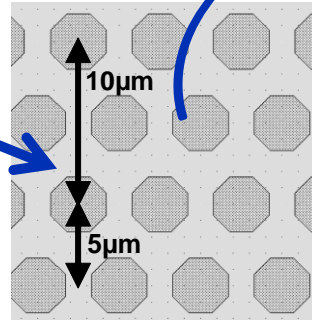
3D technology enablers

- **Through Silicon Via** formation, passivation and metallization.
- **Wafer thinning**: grinding, chemical etching...
 - via has aspect ratio (depth vs. width) \square wafer thinning!
- **High precision alignment** tool: Die to wafer or wafer to wafer.
- **Inter-Tier Bonding**.
 - face to face / face to back.
 - polymer bonding, SiO₂ bond, CuSn eutectic, metal direct DBI, Cu thermocompression...

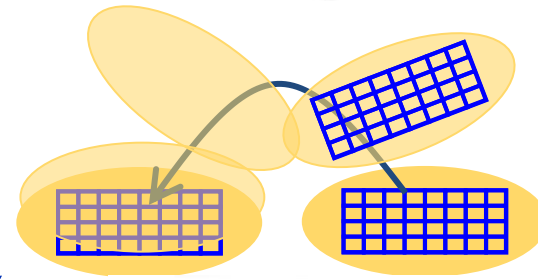
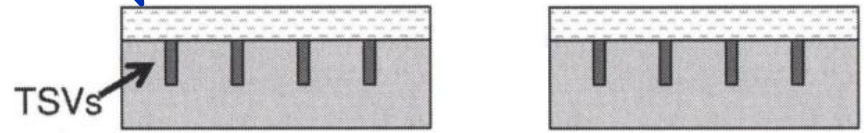


3D Tezzaron foundry process

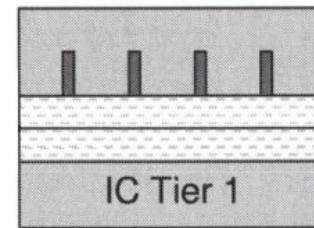
Each wafer has special interface – “bond interface” - for electrical and mechanical inter-tier connection.



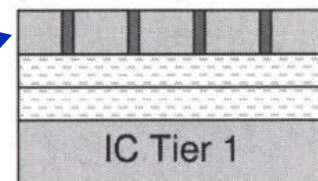
1. FEOL or BEOL TSVs



2. aligned F2F bonding

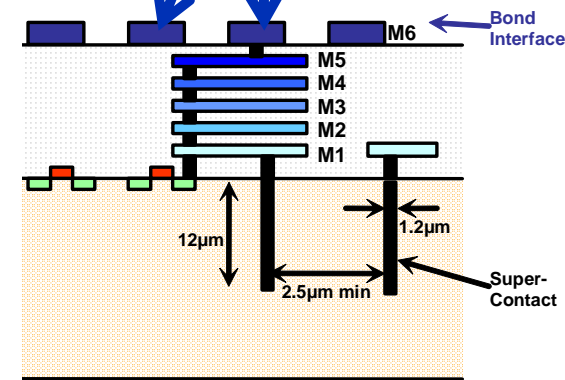


3. wafer thinning & backside processing

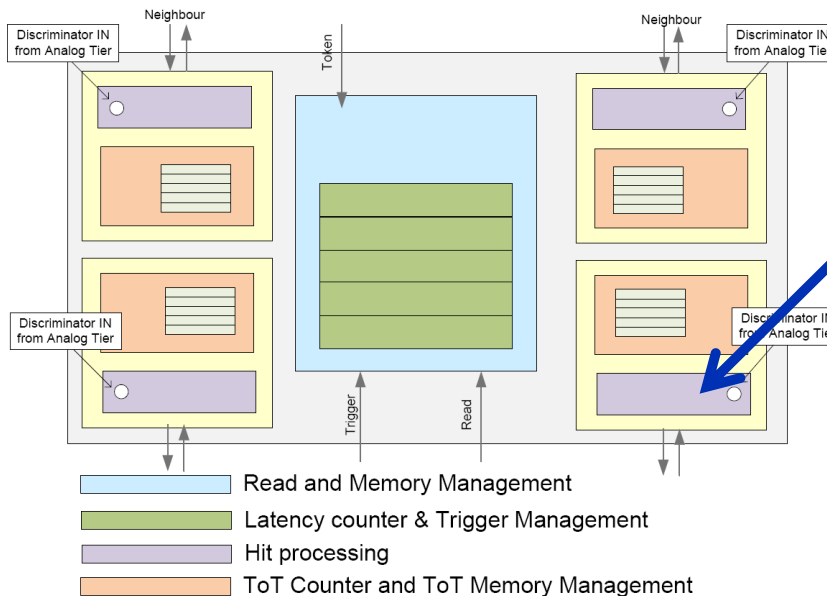
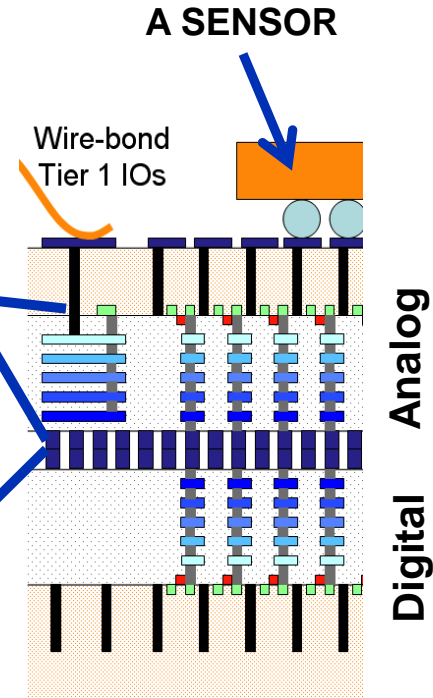
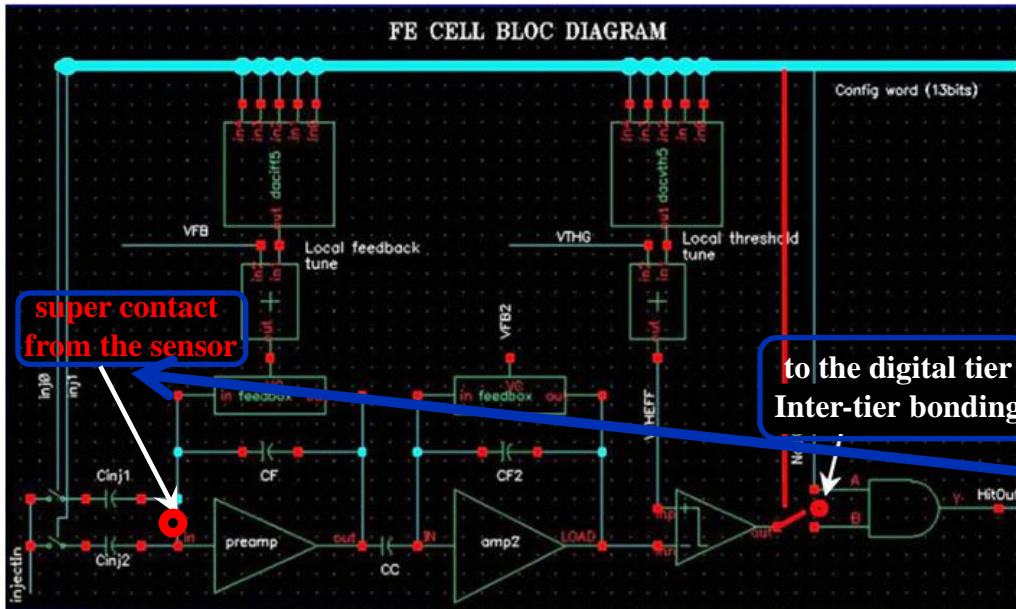


Wafers are placed one on top of another and aligned to match Bond interfaces of both tiers.

After bonding top wafer is thinned to 12 µm and diced. Thinning is needed to access TSVs

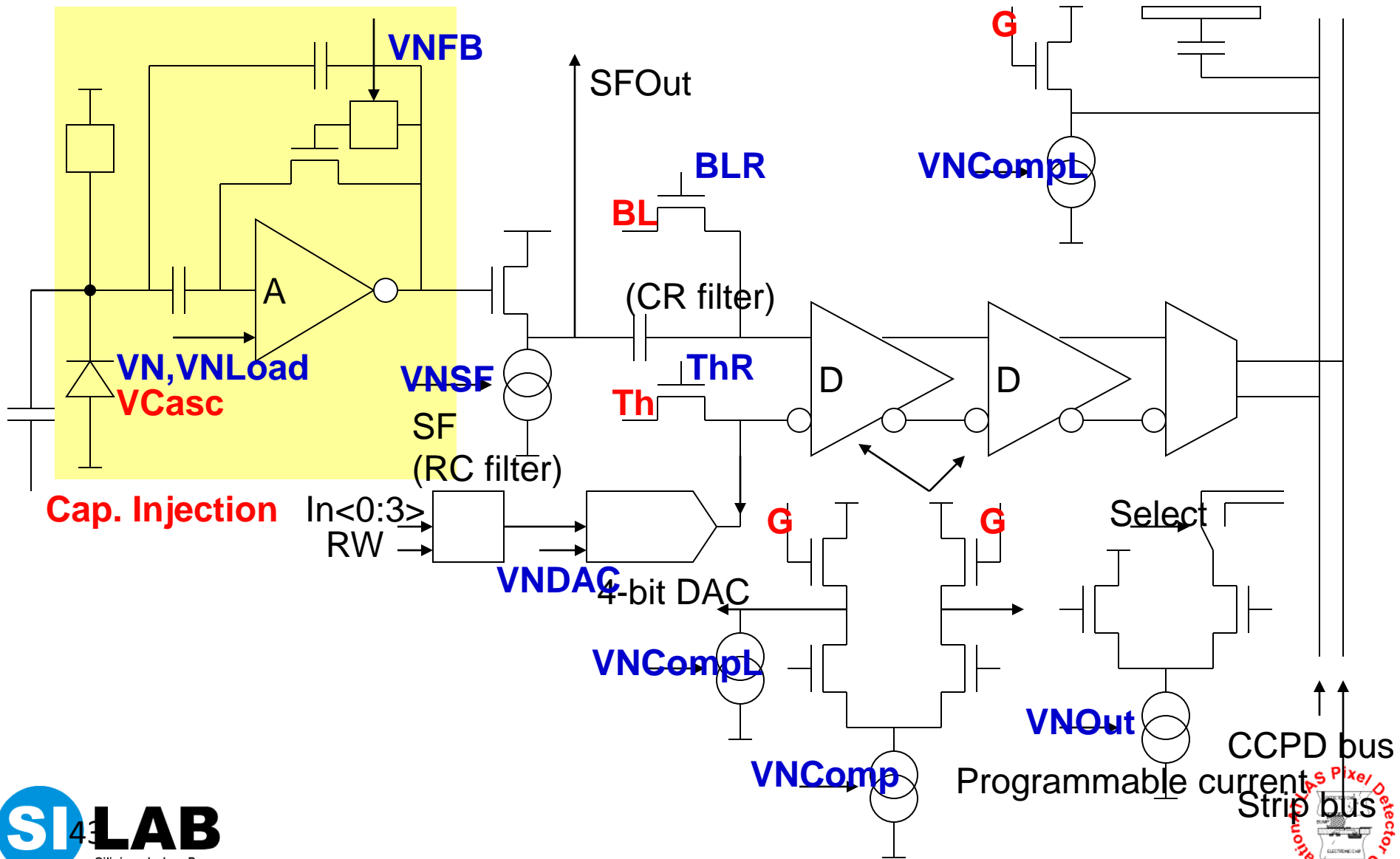


Analog and Digital Tier

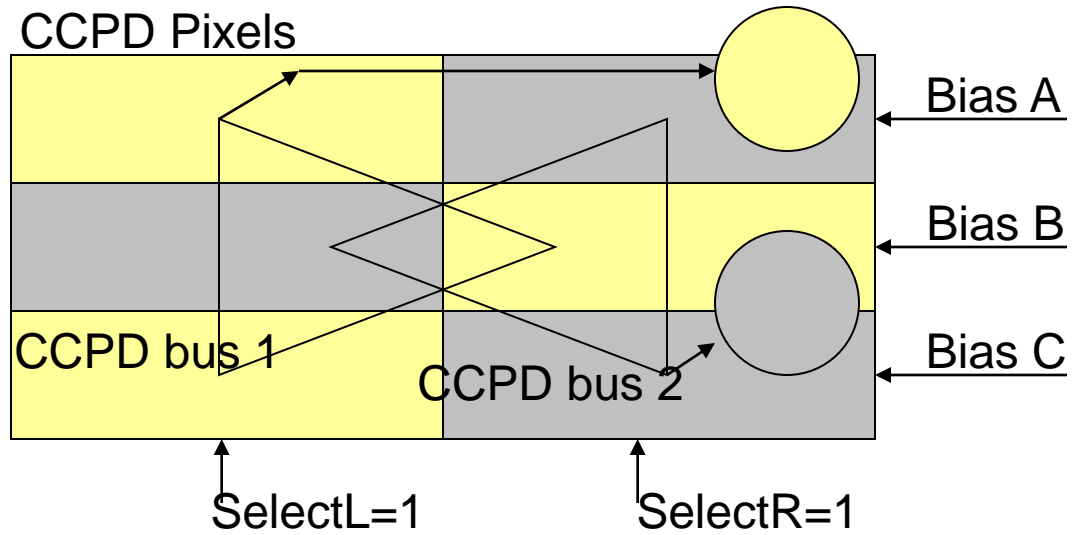


Analog pixel chain and 4-pixel Region derived from FE-I4

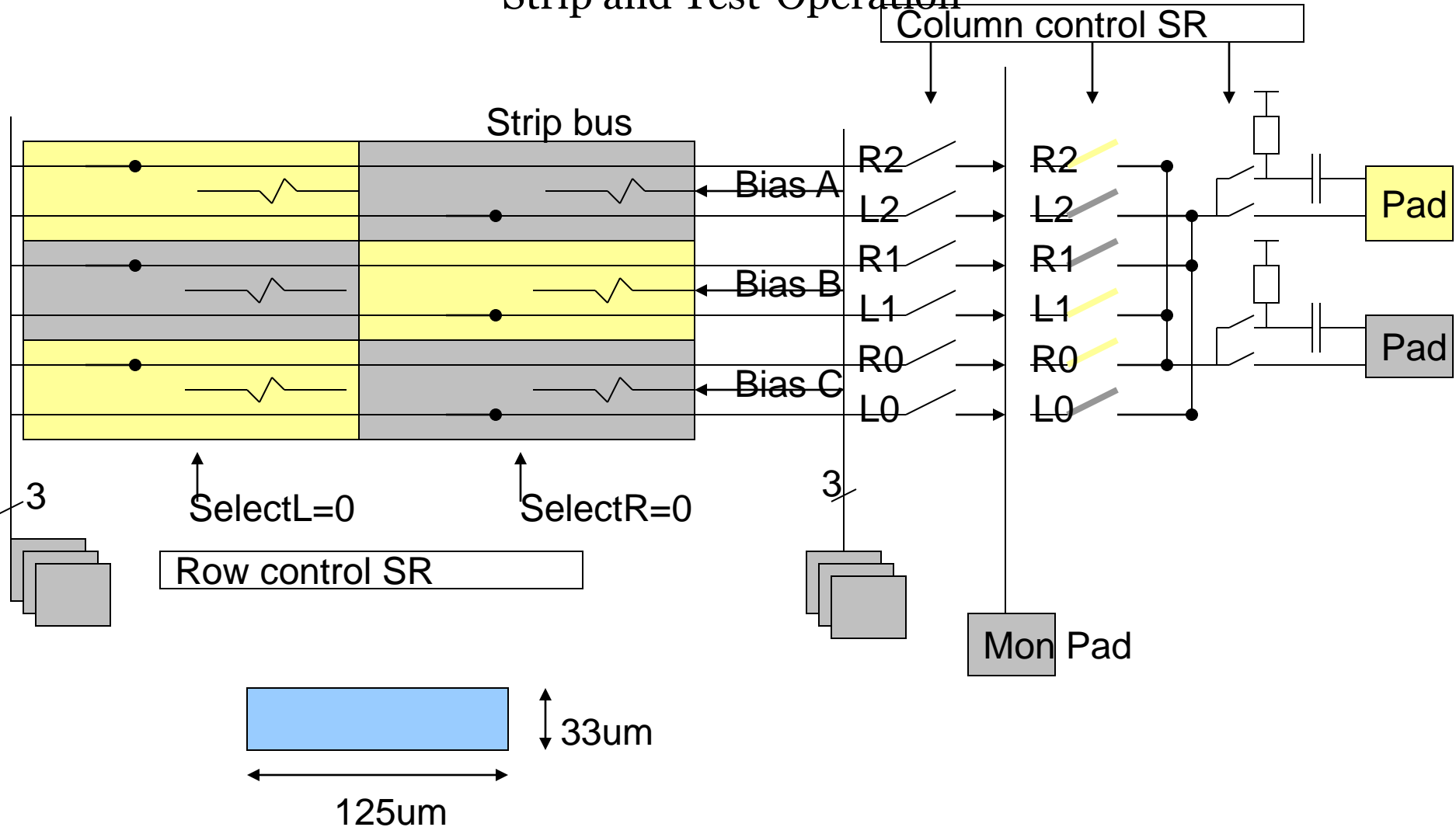
Pixel electronics - Normal



CCPD Operation



Strip and Test-Operation



Simulation results

13 dec 2011

